

ASBEST

A 7-Beryllium electron capture Study for nuclear and solid state physics



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Optical Characterization of Implantation Defects: the case study of sulphur implanted silicon

NPMET Summer School, Rome

What is LUMINESCENCE?

IUPAC says the spontaneous emission of radiation from an electronically excited species not in equilibrium with its environment

But there are several modes to excite radiation emission



Chemiluminescence

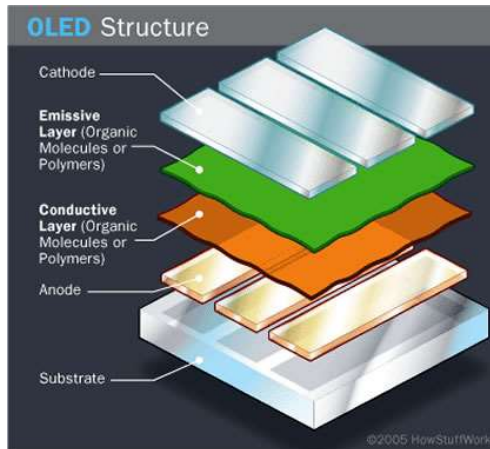
as a result of a chemical reaction



Bioluminescence

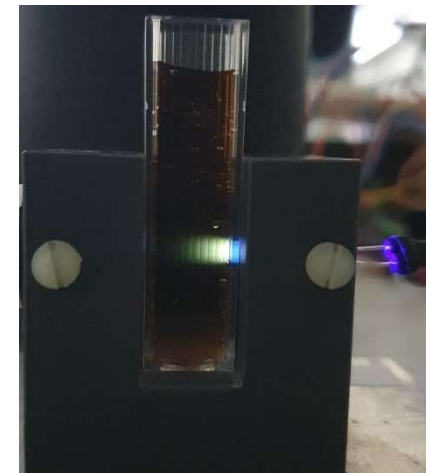
a result of biochemical reactions in a living organism

Electroluminescence



a result of an electric current passed through a substance

Photoluminescence



Optical Characterization of Implantation Defects

What is Cathodoluminescence?

Definition

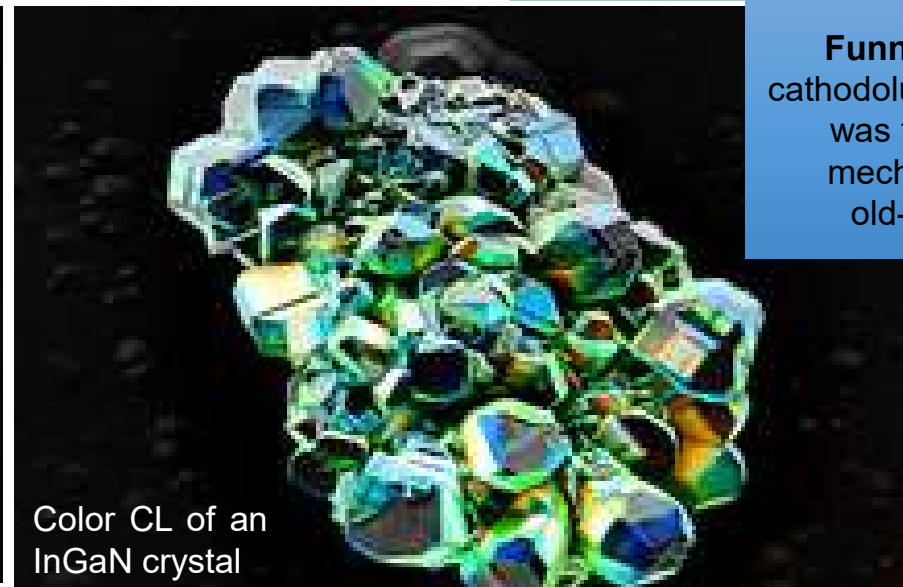
Cathodoluminescence is the physical process by which a system, excited by **high energy impinging electrons**, emits photons during relaxation to a lower energy state.

Main applications

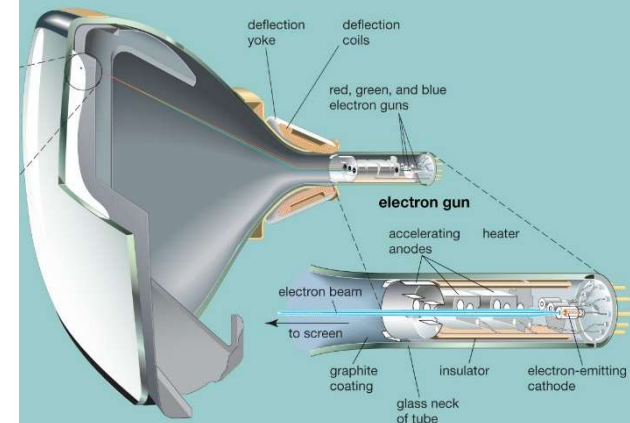
Geology / Gemology



Material Science



Funny Notes:
Defined as cathodoluminescence because electrons were called cathode rays



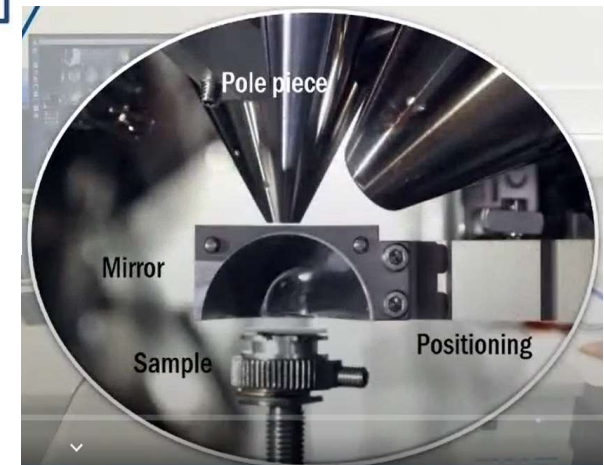
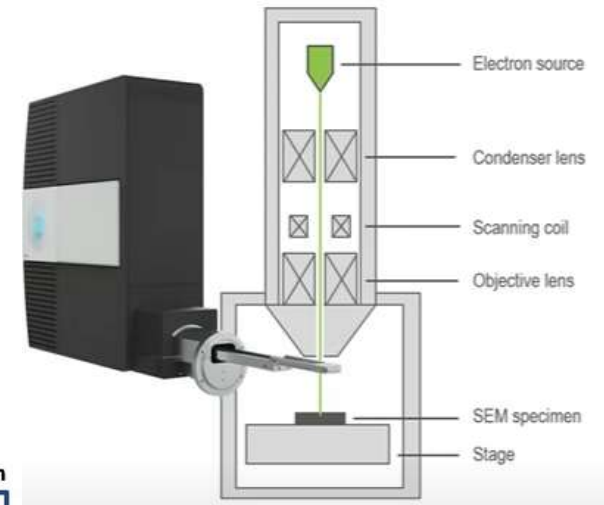
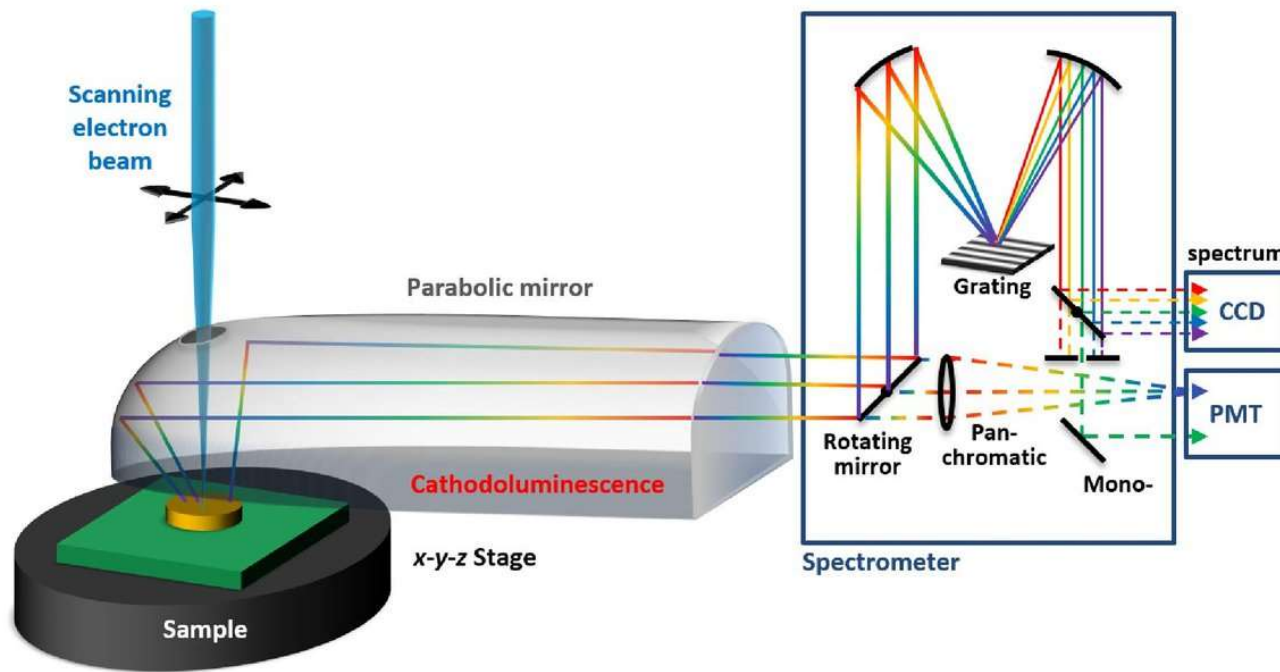
Funny Notes:
cathodoluminescence was the basic mechanism of old-gen TV

Optical Characterization of Implantation Defects

How to acquire Cathodoluminescence?

CL experiments can be carried out in:

- Scanning Electron Microscope (SEM)

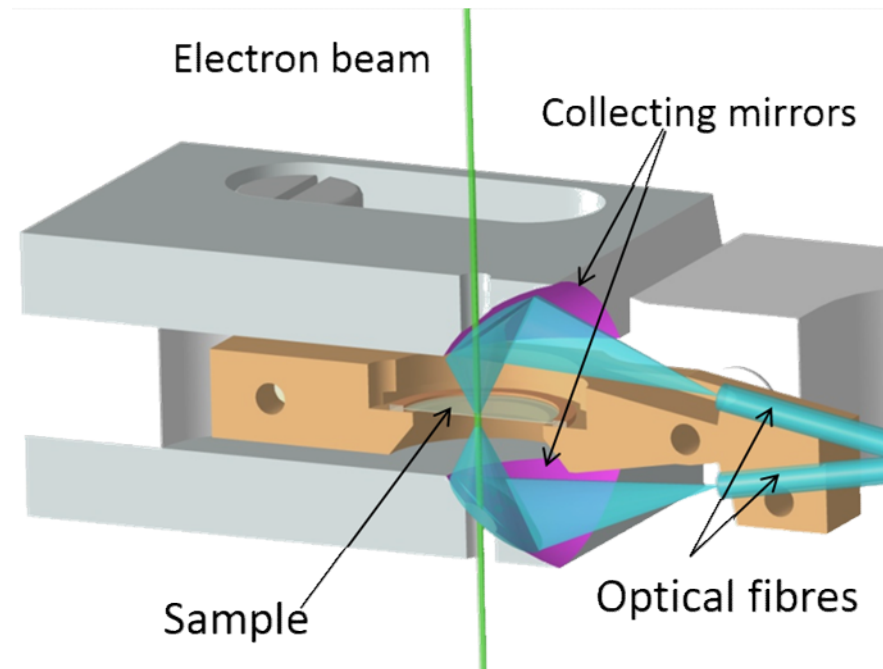
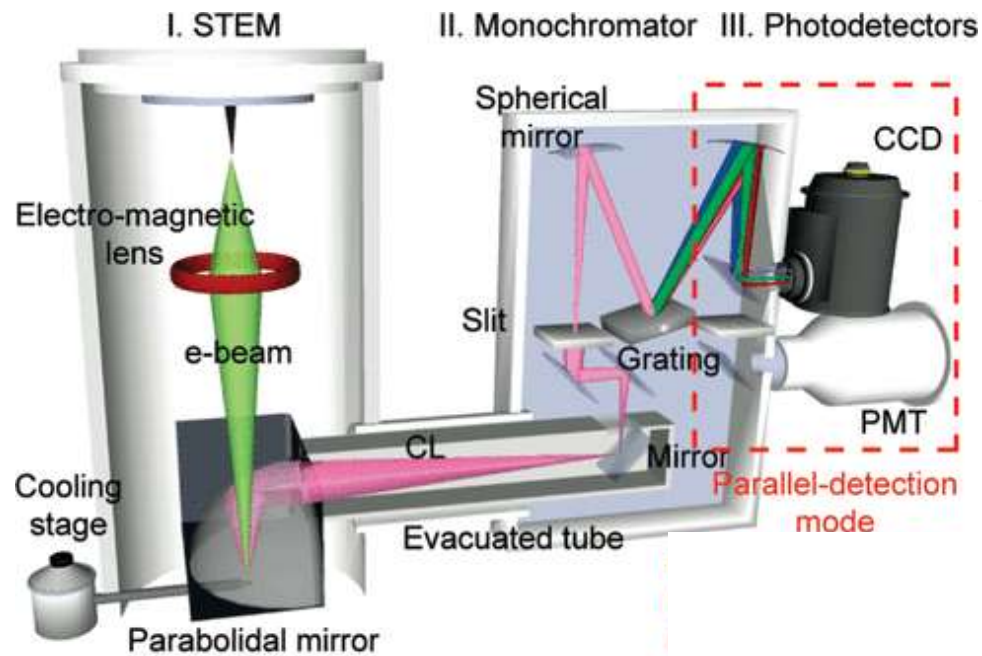


Optical Characterization of Implantation Defects

How to acquire Cathodoluminescence?

CL experiments can be carried out in:

- Scanning Transmission Electron Microscope (STEM)



How to acquire Cathodoluminescence spectrum or map?

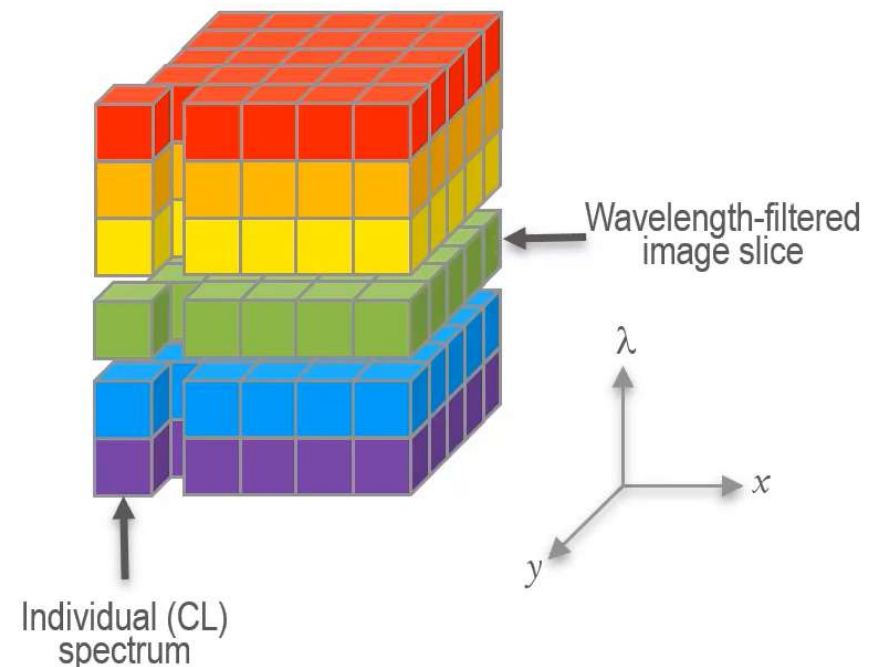
Hyperspectral Data Cube (Spectrum Image)

A 3D dataset (data cube) containing both spatially- and spectrally- resolved information

- A two-dimensional array of spectra
- An aligned stack of wavelength-filtered images; typically > 20 wavelength slices

Advantages include:

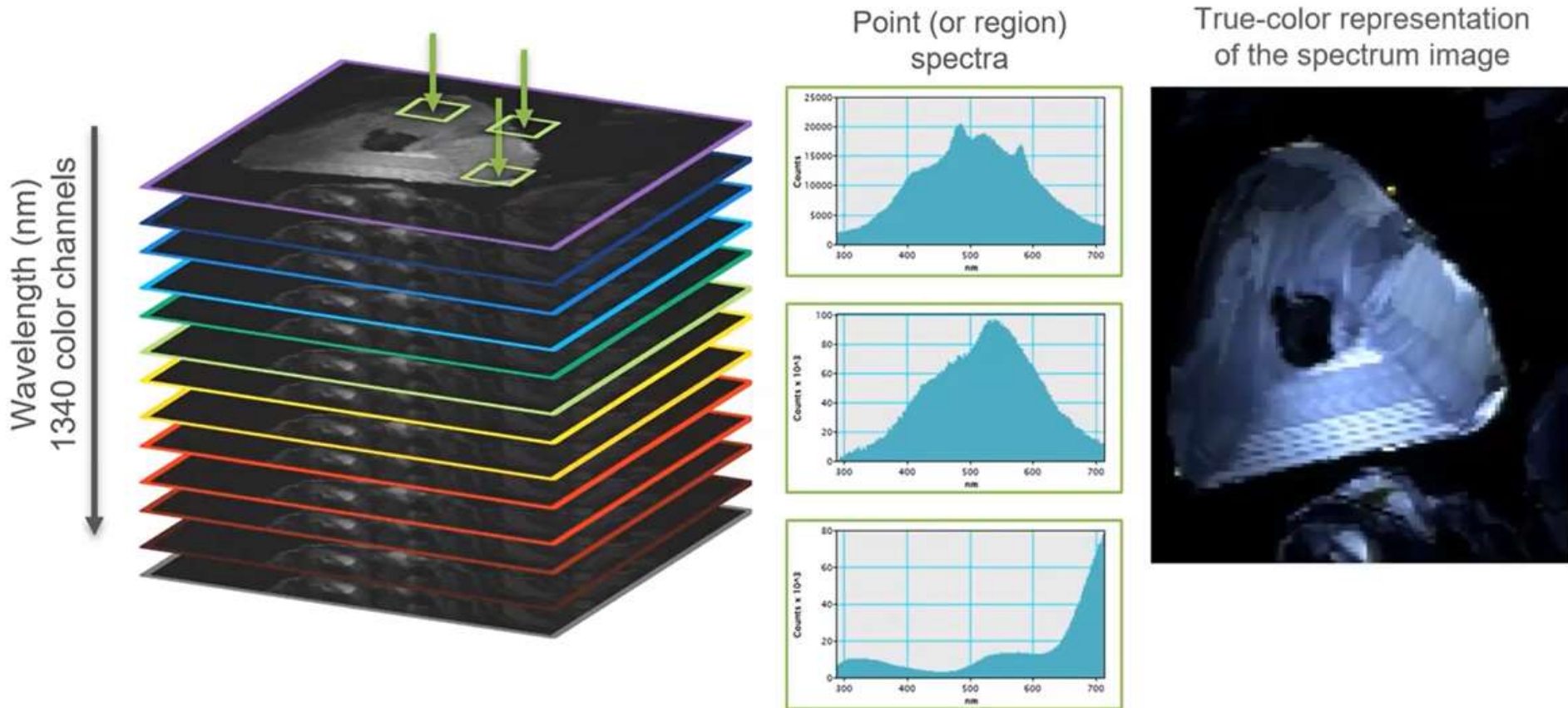
- All spatial and spectral information captured; no *a priori* knowledge required
- Spectra or wavelength-filtered images may be extracted in post processing analysis
- Quantitative mapping using mathematical processing; correlation with other hyperspectral data techniques



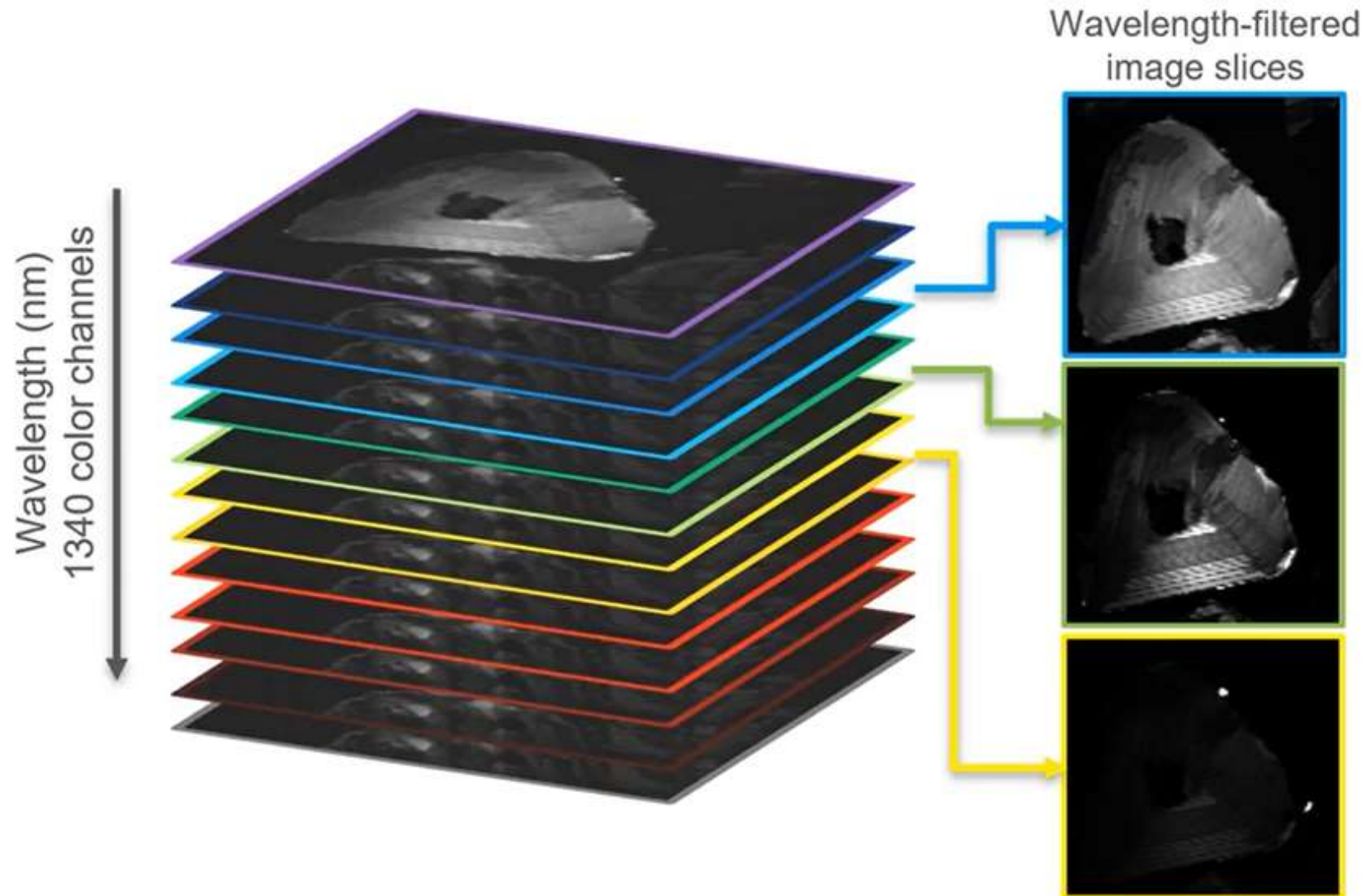
Hyperspectral 'data cube'

Optical Characterization of Implantation Defects

How to acquire a Cathodoluminescence spectrum?



How to acquire a Cathodoluminescence map?



What are the ADVANTEGES of CL spectroscopy and imaging?

Detection of luminescence with different nature and their interaction

Correlative analysis with other electron excitation based techniques

**Electron penetration depth is variable:
depth-resolved studies, imaging buried structures**

Nanoscale lateral resolution based on electron excitation

***In-Situ* CL analysis of electron irradiated materials**

CL study of ion implanted materials

The case study: the luminescence of sulphur implanted silicon

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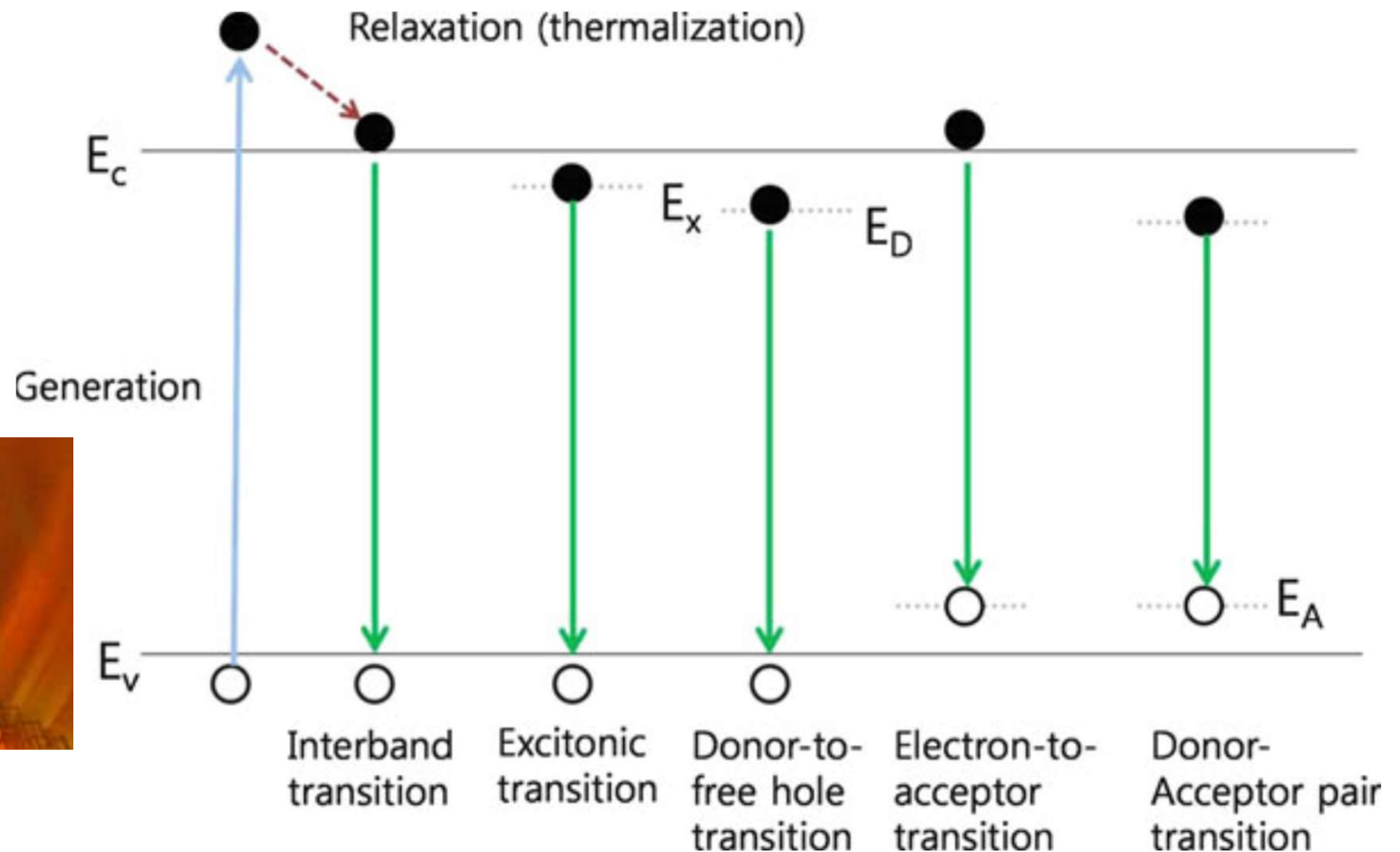
Detection of luminescence with different nature and their interaction

High energy electron probe allows the excitation of insulators and wide bandgap semiconductor

SiO_2 $E_g \approx 9\text{eV}$

hBN $E_g \approx 6\text{eV}$

Ga_2O_3 $E_g \approx 5.5\text{eV}$



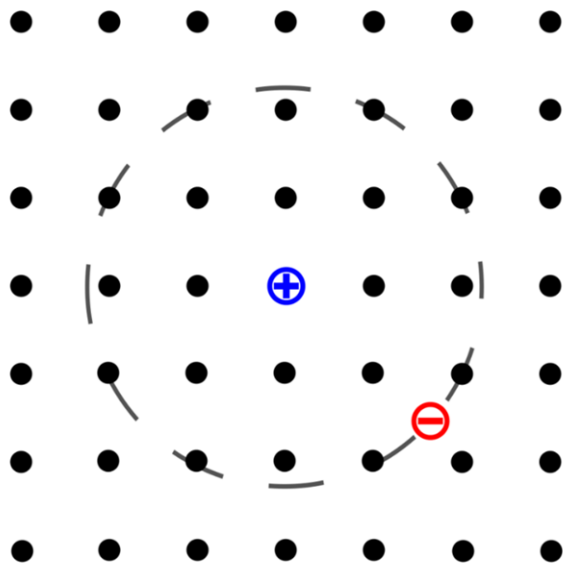
Optical Characterization of Implantation Defects

Detection of luminescence with different nature and their interaction

What is an exciton?

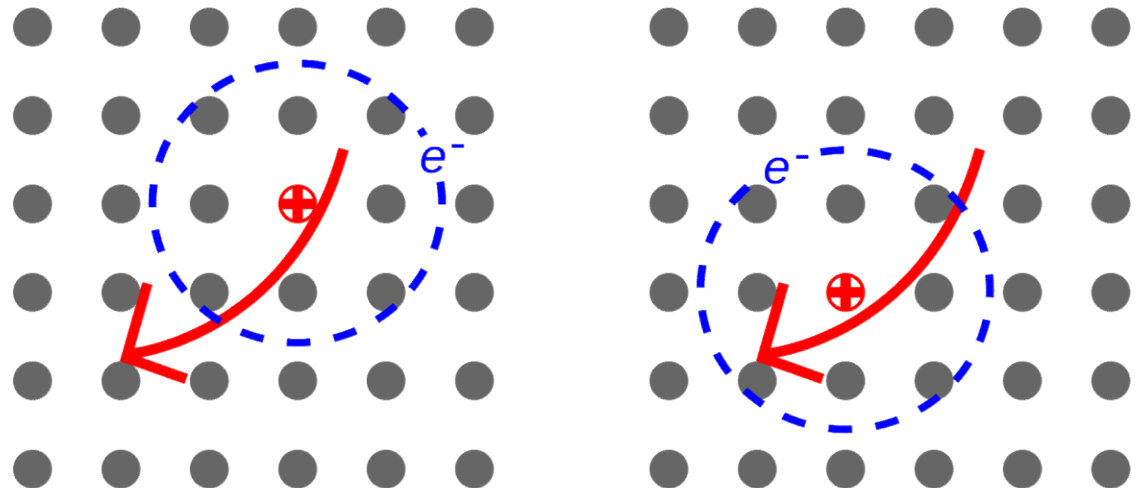
An exciton is a bound state of an electron and an hole which are attracted to each other by the electrostatic Coulomb force.

Frenkel exciton



In materials with a relatively **small dielectric constant**, the Coulomb interaction between electron and hole may be strong and the excitons thus tend to be small, of the same order as the size of the unit cell.

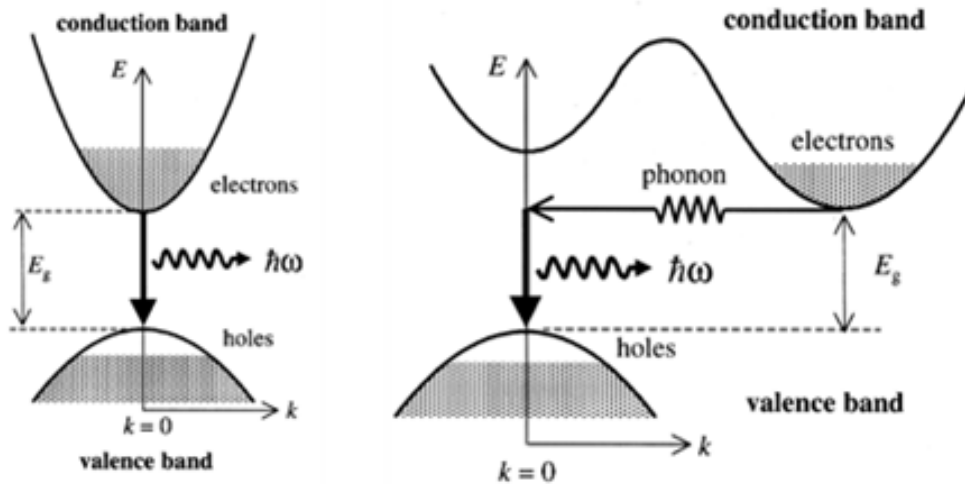
Wannier – Mott exciton



In semiconductor, the **high dielectric constant** decreases the Coulomb interaction between the electron and the hole therefore the exciton radius is bigger than the unit cell.

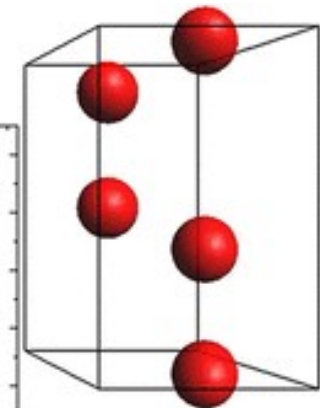
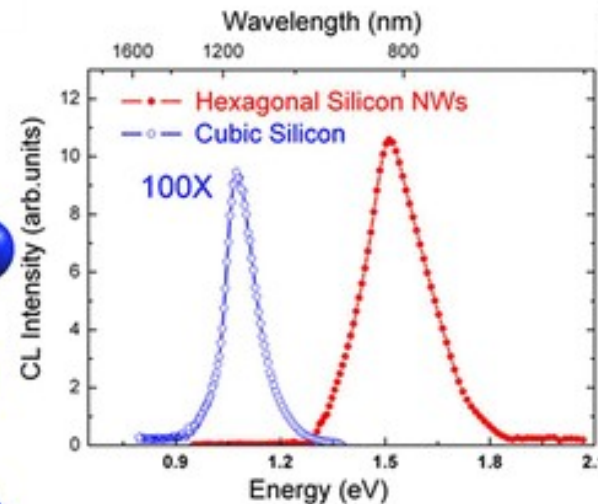
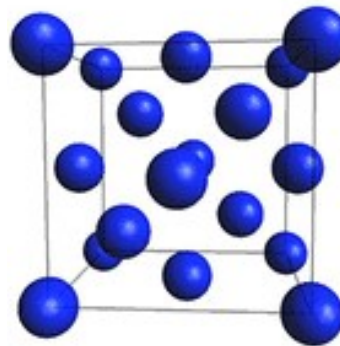
Optical Characterization of Implantation Defects

Detection of luminescence with different nature and their interaction



In CL experiments is possible to detect indirect bandgap transition due to the local generation of thermal phonons.

The direct bandgap radiative recombination are more intense than the ones related to indirect bandgap: the example of silicon in different crystalline lattice.

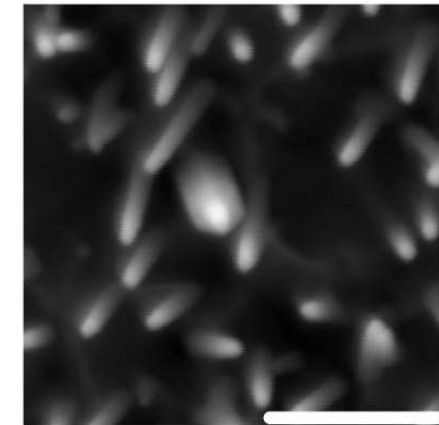
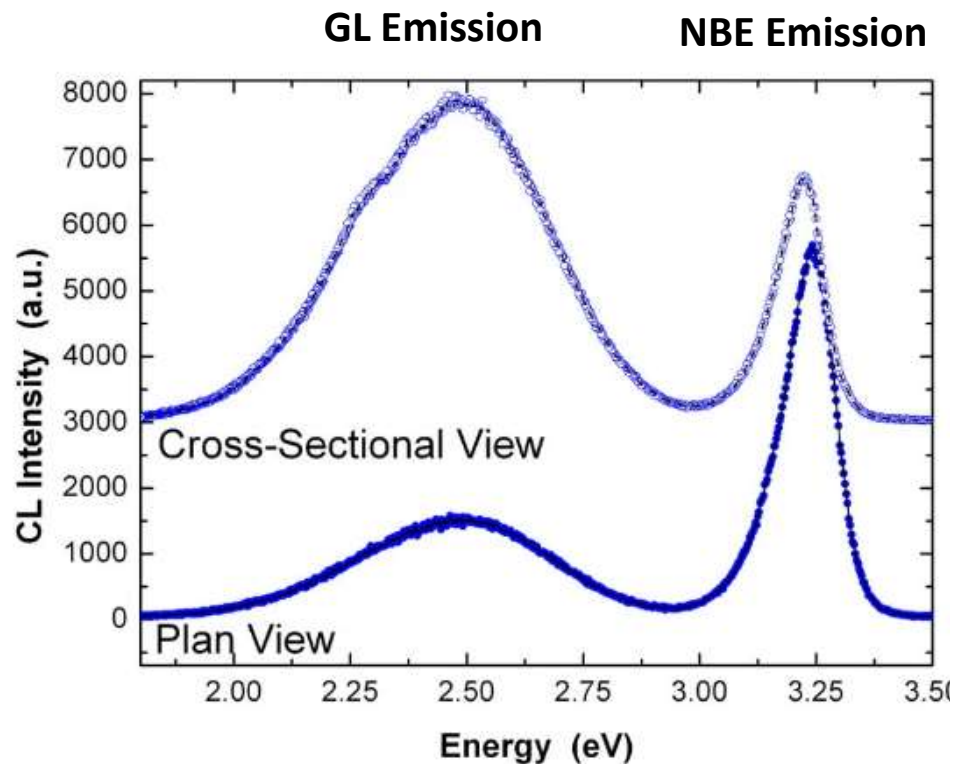


Nano Lett. 2013, 13, 5900–5906

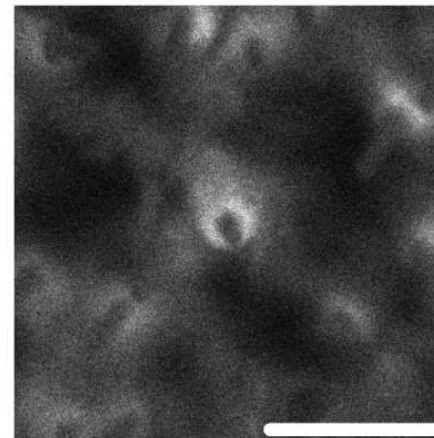
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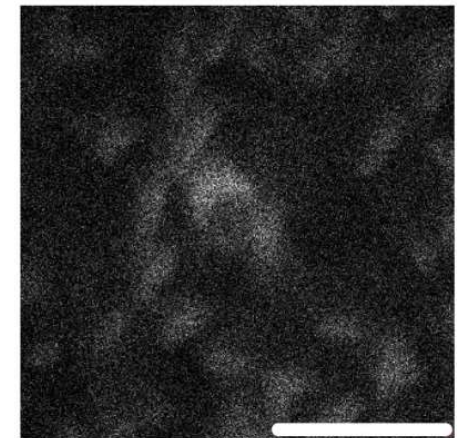
SEM-CL: Detection of defect related emission (GL) on lateral surface of ZnO NanoRod



a) SE 500 nm



b) NBE MonoCL



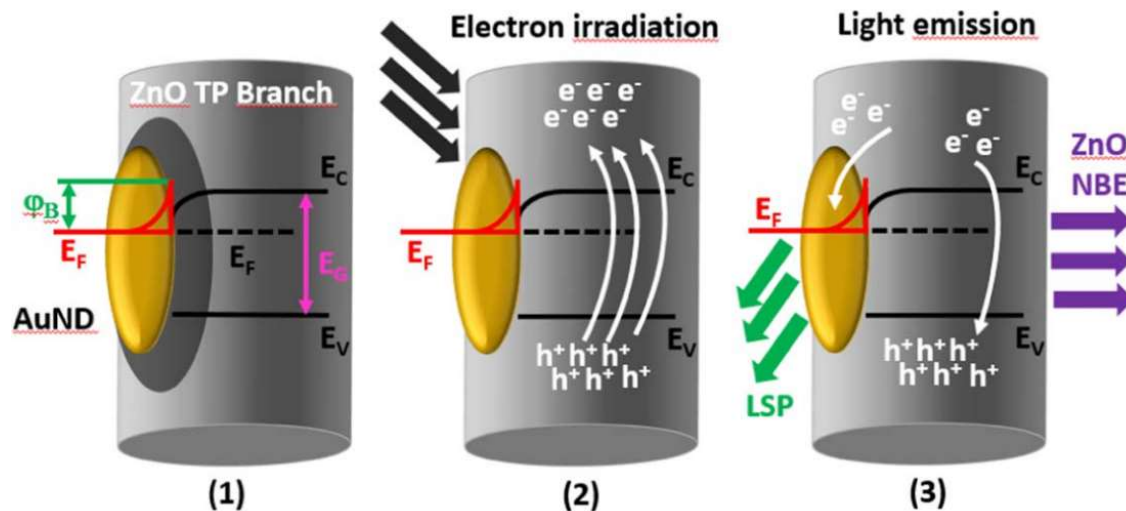
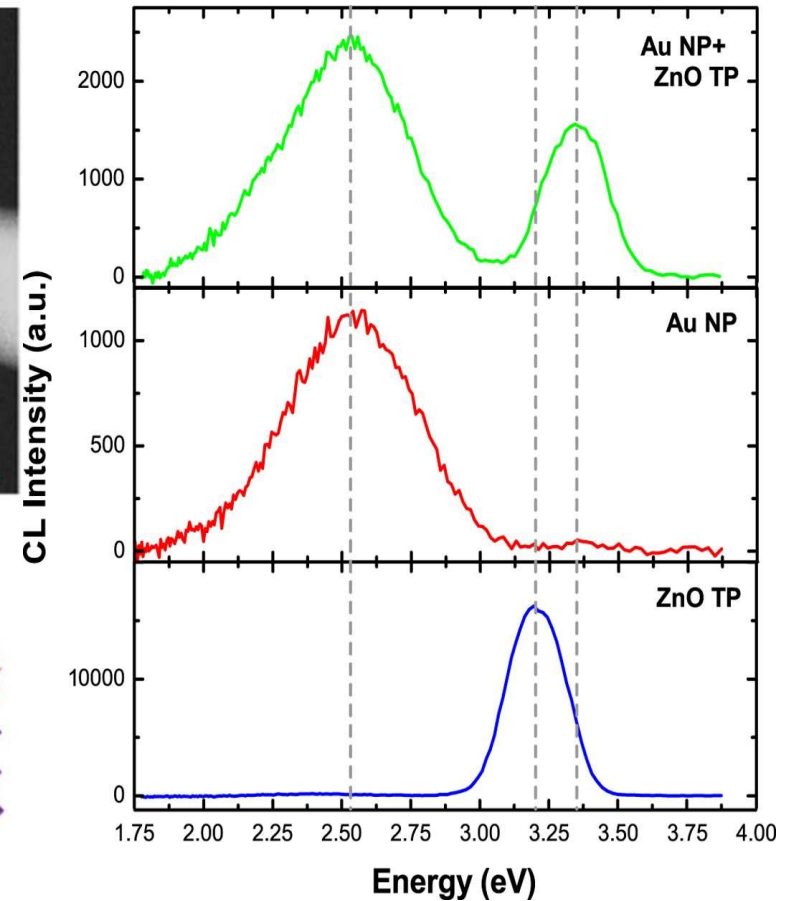
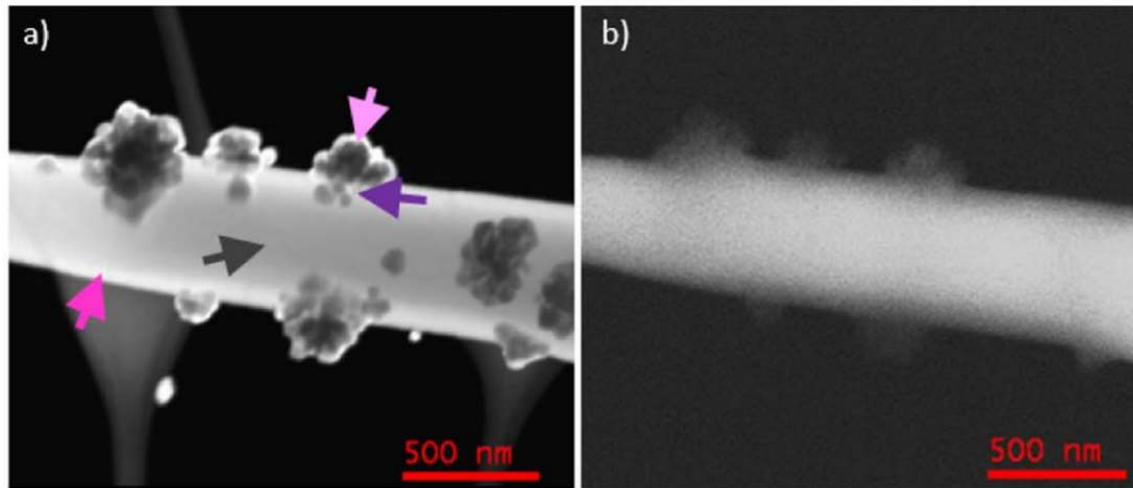
c) GL MonoCL

Scientific Reports **4**, 5158 (2014)

Optical Characterization of Implantation Defects

Detection of luminescence with different nature and their interaction

STEM-CL: Interaction of ZnO exciton with gold nano-aggregate surface plasmon.



Nano Express 2 014004 (2021)

What are the ADVANTEGES of CL spectroscopy and imaging?

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Correlative analysis with other electron excitation based techniques

**Electron penetration depth is variable:
depth-resolved studies, imaging buried structures**

Nanoscale lateral resolution based on electron excitation

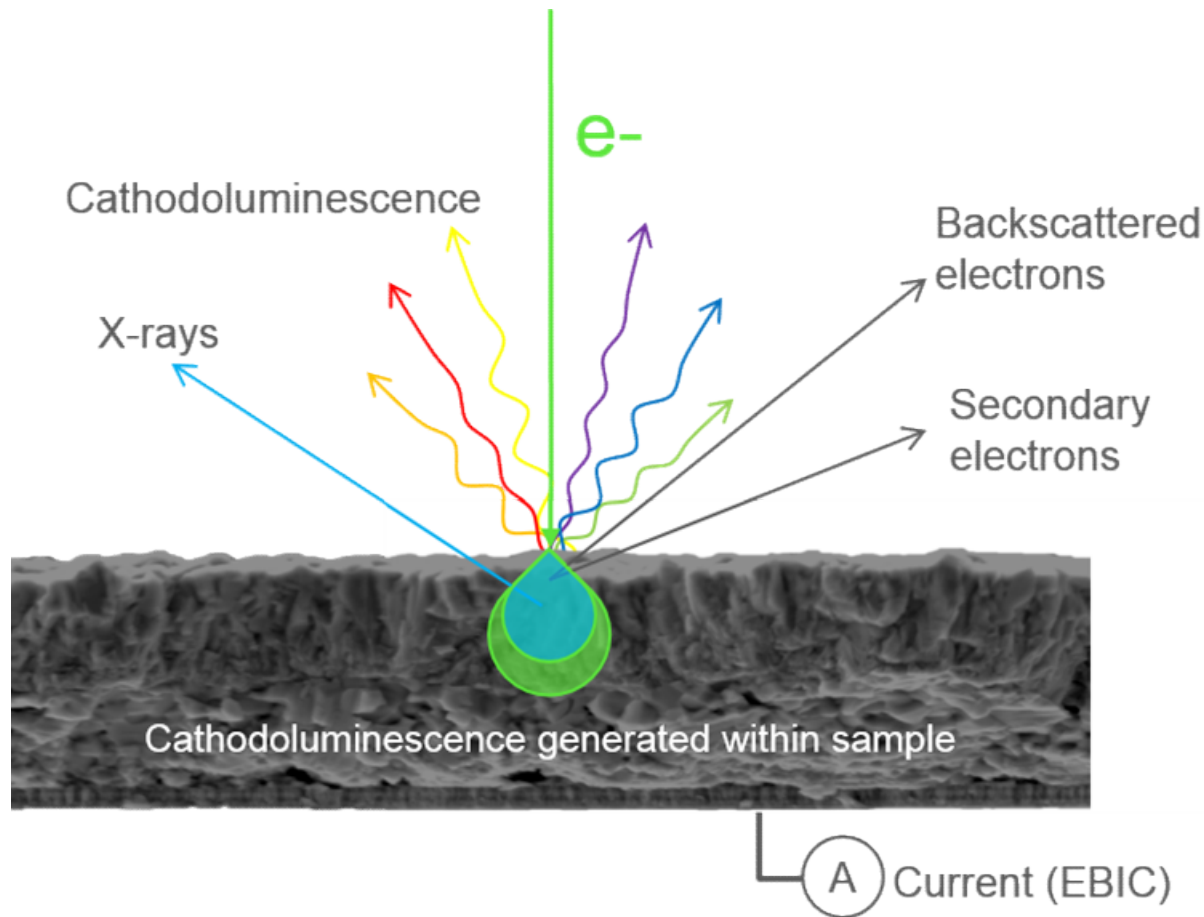
***In-Situ* CL analysis of electron irradiated materials**

CL study of ion implanted materials

The case study: the luminescence of sulphur implanted silicon

Optical Characterization of Implantation Defects

Correlative analysis with other electron excitation based techniques



The interaction of the primary electron beam with the sample gives rise to several results (SE, BSE, X-ray), therefore it is possible to take advantages of the different signals to carry out correlative analyses in terms of:

- **morphology,**
- **composition**
- **optical properties.**

Optical Characterization of Implantation Defects

Correlative analysis with other electron excitation based techniques

Composition Mapping of Cadmium Telluride/Sulphide Alloy

- CL maps the bandgap
- Estimate Sulphur content $\text{CdTe}_{1-x}\text{S}_x$

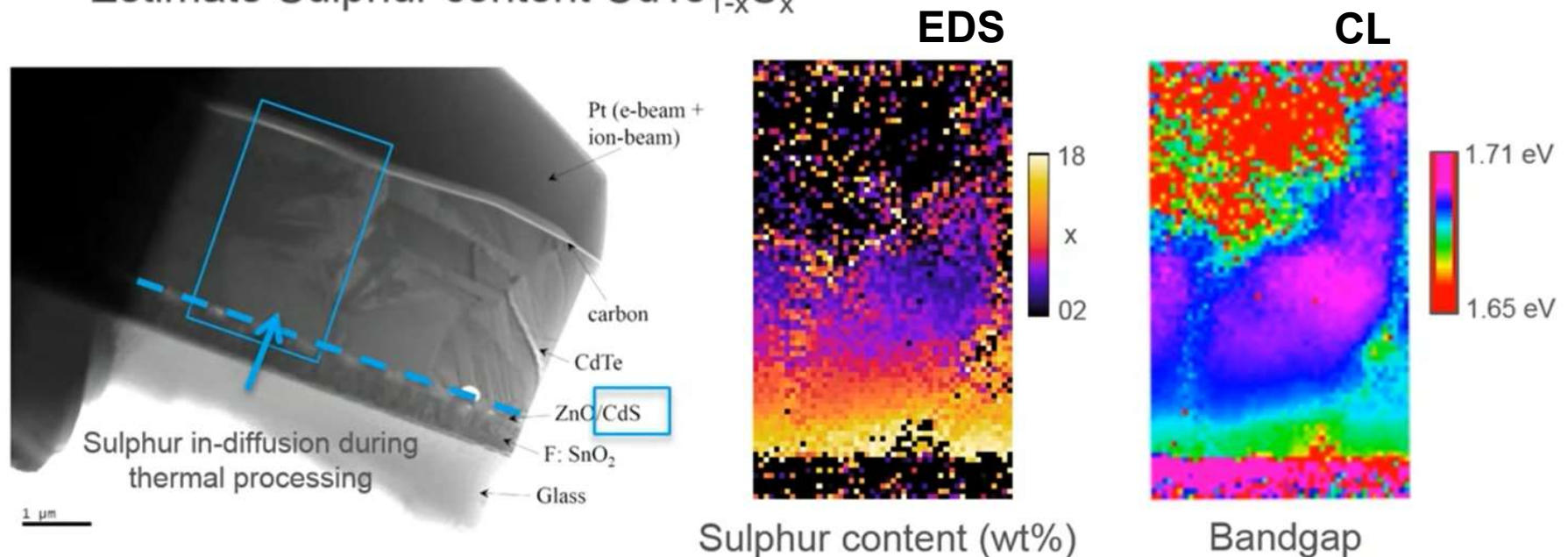


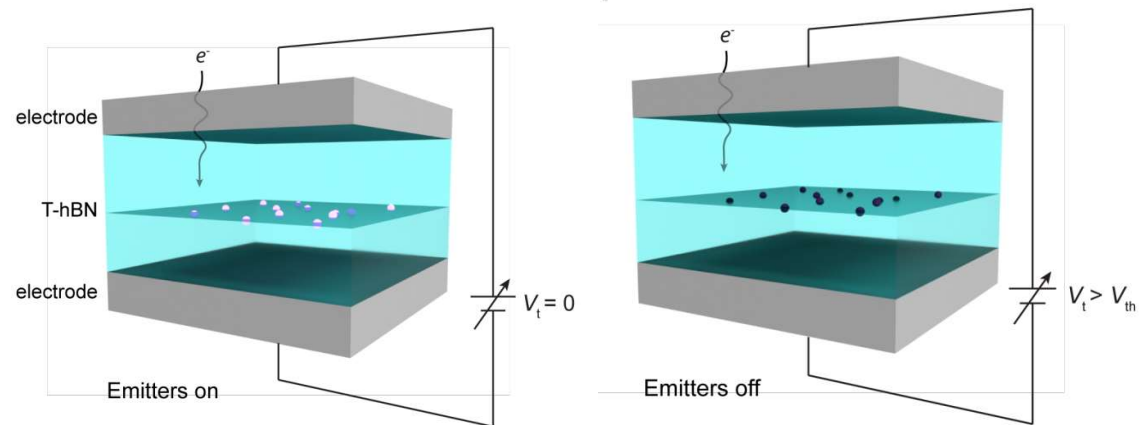
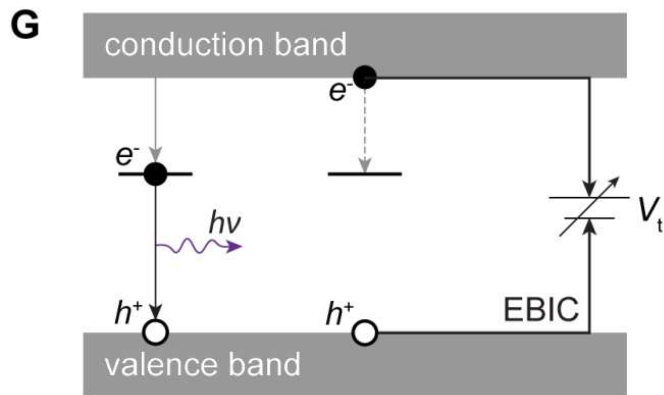
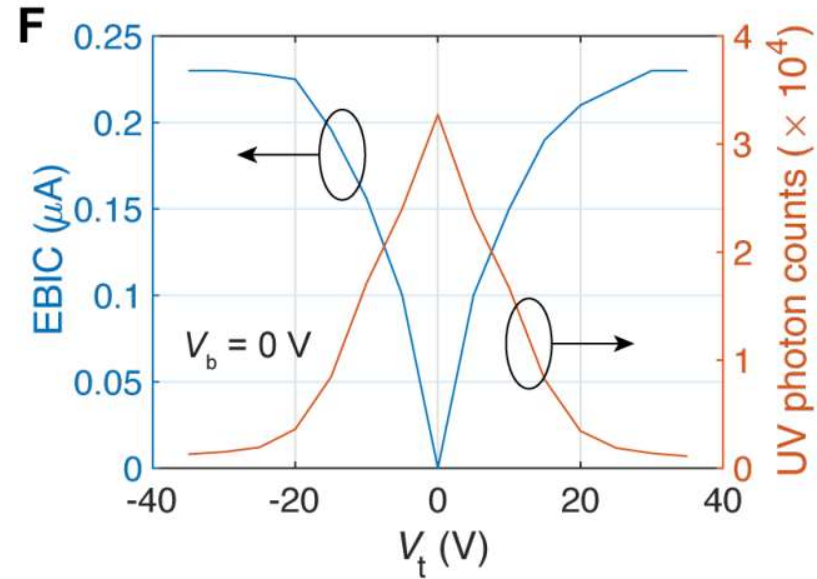
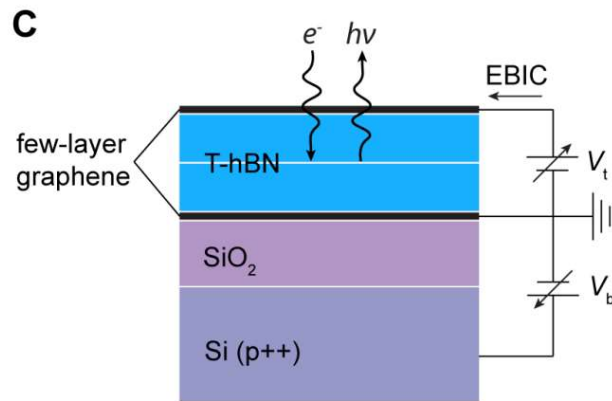
Image information: Band gap map of $\text{CdTe}_{1-x}\text{S}_x$ alloy extracted by Gaussian fitting from CL spectrum-image, courtesy of Dr B. Mendis, Durham University

Optical Characterization of Implantation Defects

Correlative analysis with other electron excitation based techniques

This is not true for every SEM base techniques, in fact EBIC and CL are based on two different way to collect the electron excited carriers:

Nature Materials **21**, 896–902 (2022)



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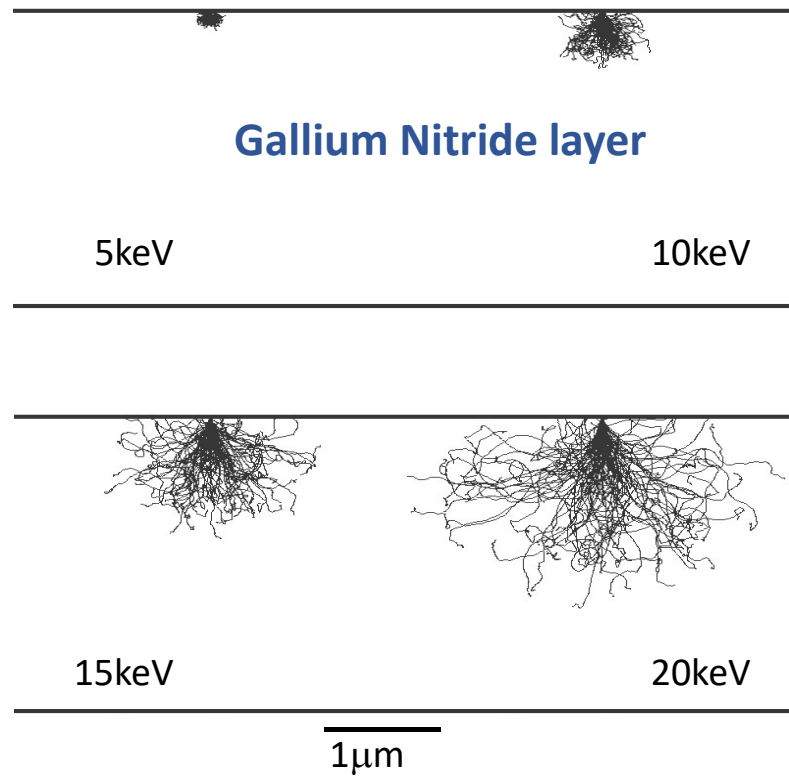
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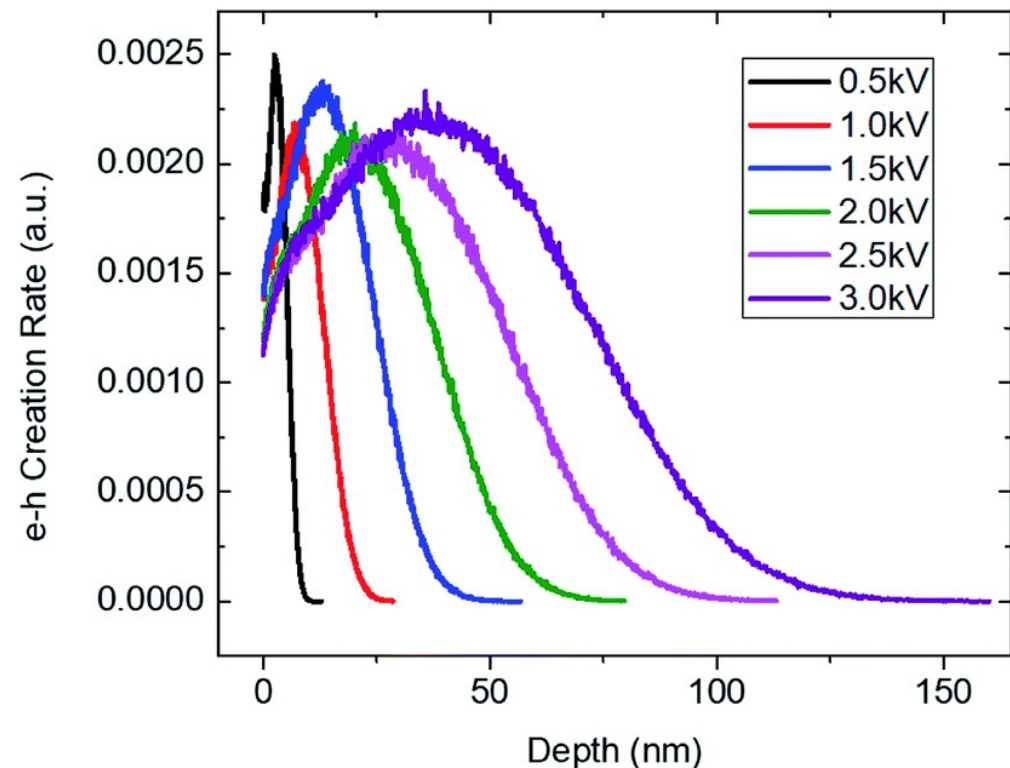
Optical Characterization of Implantation Defects

Electron penetration depth is variable

Generation volume in a material



It is possible to simulate the stochastic scattering events of the primary electron beam with atoms composing a material depending on the material density by means of classical Monte Carlo Simulation (MCS).



Optical Characterization of Implantation Defects

How to perform Monte Carlo simulations

2. Casino

A free software package for Monte Carlo simulation of electron trajectories in solids



Authors: Dominique Drouin, Alexandre Real Couture, Raynald Gauvin, Pierre Hovington, Paula Homy and Hendrix Demers

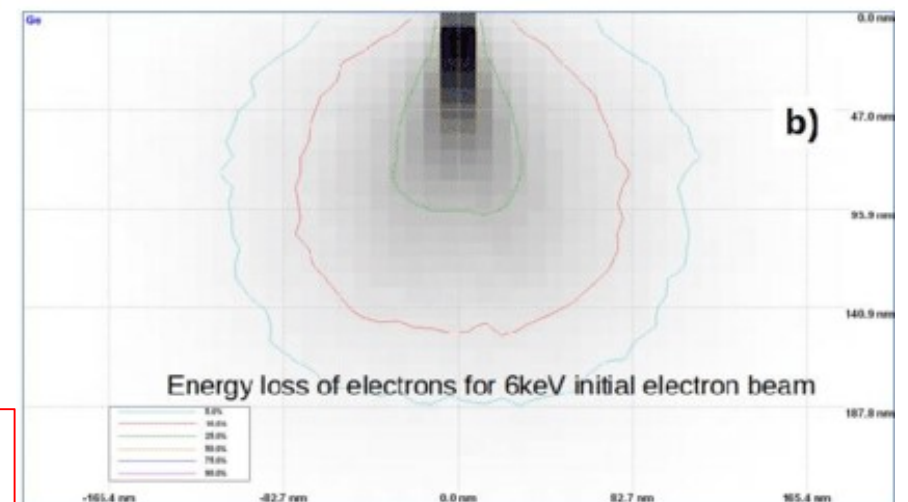
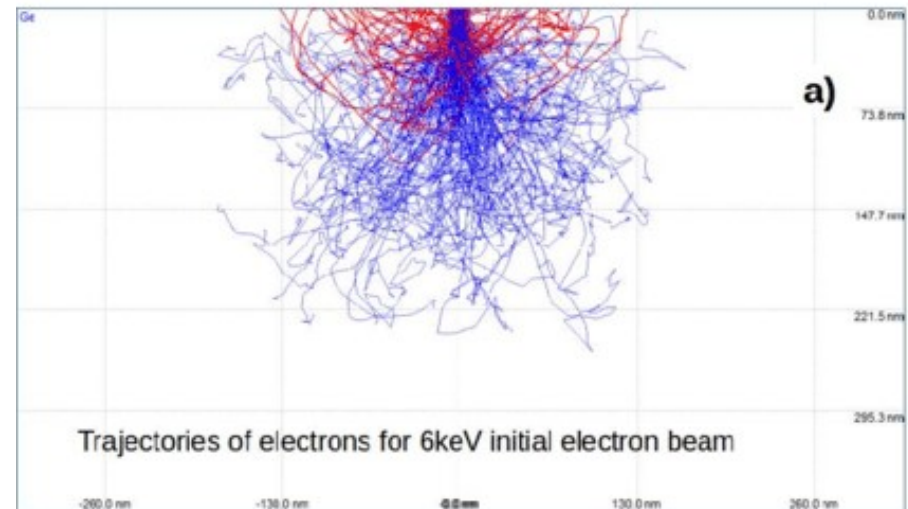
Platform: Windows

Citations:

1. P. Hovington, D. Drouin and R. Gauvin, "CASINO: A New Monte Carlo Code in C Language for Electron Beam Interaction - Part I: Description of the Program", *Scanning*, **19** (1997), 1-14.
2. D. Drouin, P. Hovington and R. Gauvin, "CASINO: A New Monte Carlo Code in C Language for Electron Beam Interaction - Part II: Tabulated Values of the Mott Cross Section", *Scanning*, **19** (1997), 20-28.
3. D. Drouin, P. Hovington, R. Gauvin, D.C. Joy and N. Evans, "CASINO: A New Monte Carlo Code in C Language for Electron Beam Interaction - Part III: Stopping Power at Low Energies", *Scanning*, **19** (1997) 29-35.
4. D. Drouin, A.R.Couture, D. Joly, X. Tastet, V. Aimez and R. Gauvin, "CASINO V2.42 - A Fast and Easy-to-use Modeling Tool for Scanning Electron Microscopy and Microanalysis Users", *Scanning*, **29** (2007), 92-101.

Link: <http://www.gel.usherbrooke.ca/casino/What.html>

The last version of CASINO has a CAD based system for simulating 3D structures!



Optical Characterization of Implantation Defects

If you don't want to run Monte Carlo simulations

The maximum effective penetration depth (Grün range, R_G) to which energy dissipation (and e-h pairs generation) extends is a function of the beam energy (E_B) and of the material density (ρ). This is in general parameterized as:

$$R_G = \frac{k}{\rho} E_B^\alpha$$

For a uniform single-type material:

Everhart and Hoff (1971) derived $k=3.98 \times 10^{-2}$ and $\alpha=1.75$ valid for $5 < E_B < 25$ keV and $10 < Z < 15$,

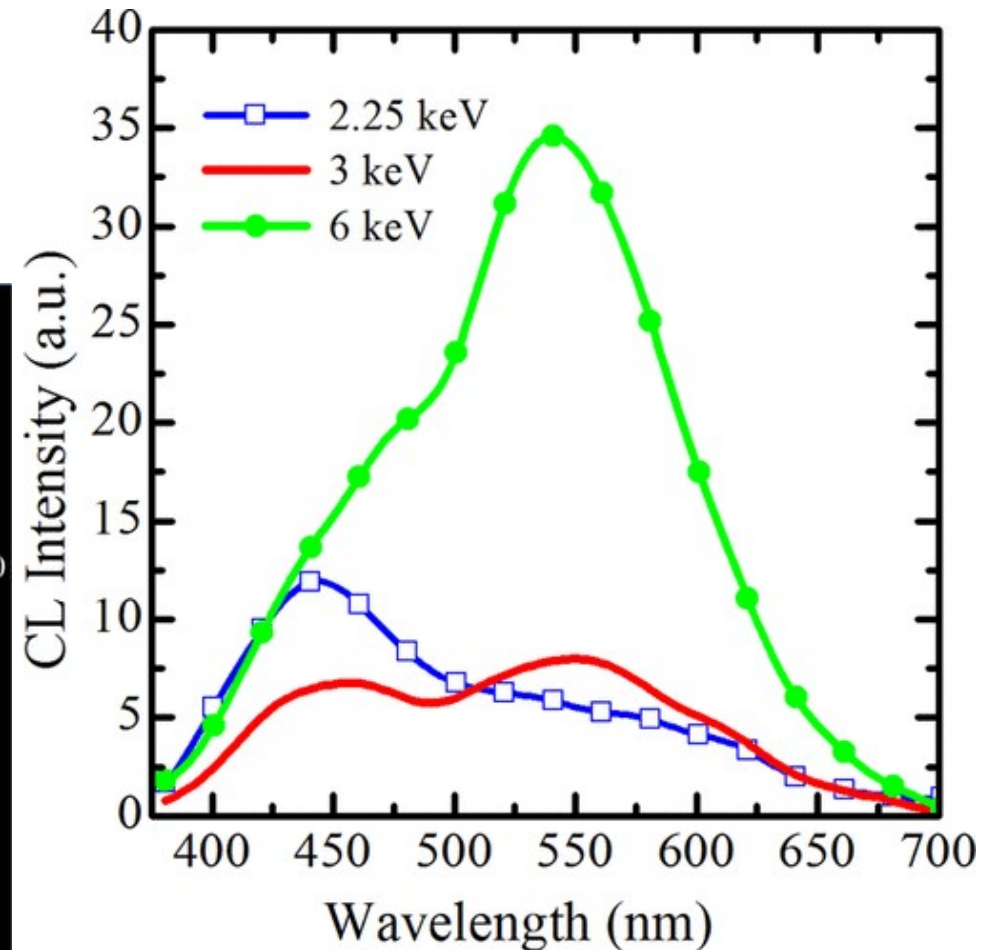
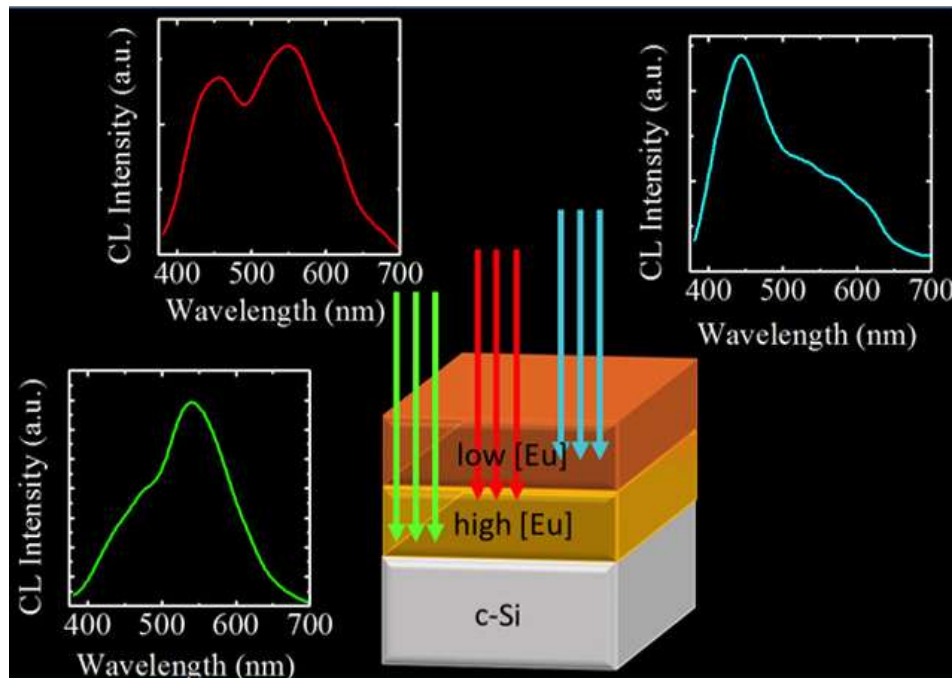
Kanaya and Okayama (1972) derived a more general expression with $\alpha=1.67$ and $k=2.76 \times 10^{-2} \times (A/Z^{0.889})$, having a wider applicability and in good agreement with experimental data.

Optical Characterization of Implantation Defects

Electron penetration depth is variable: depth-resolved studies

ACS Appl. Mater. Interfaces 2015, 7, 18201–18205

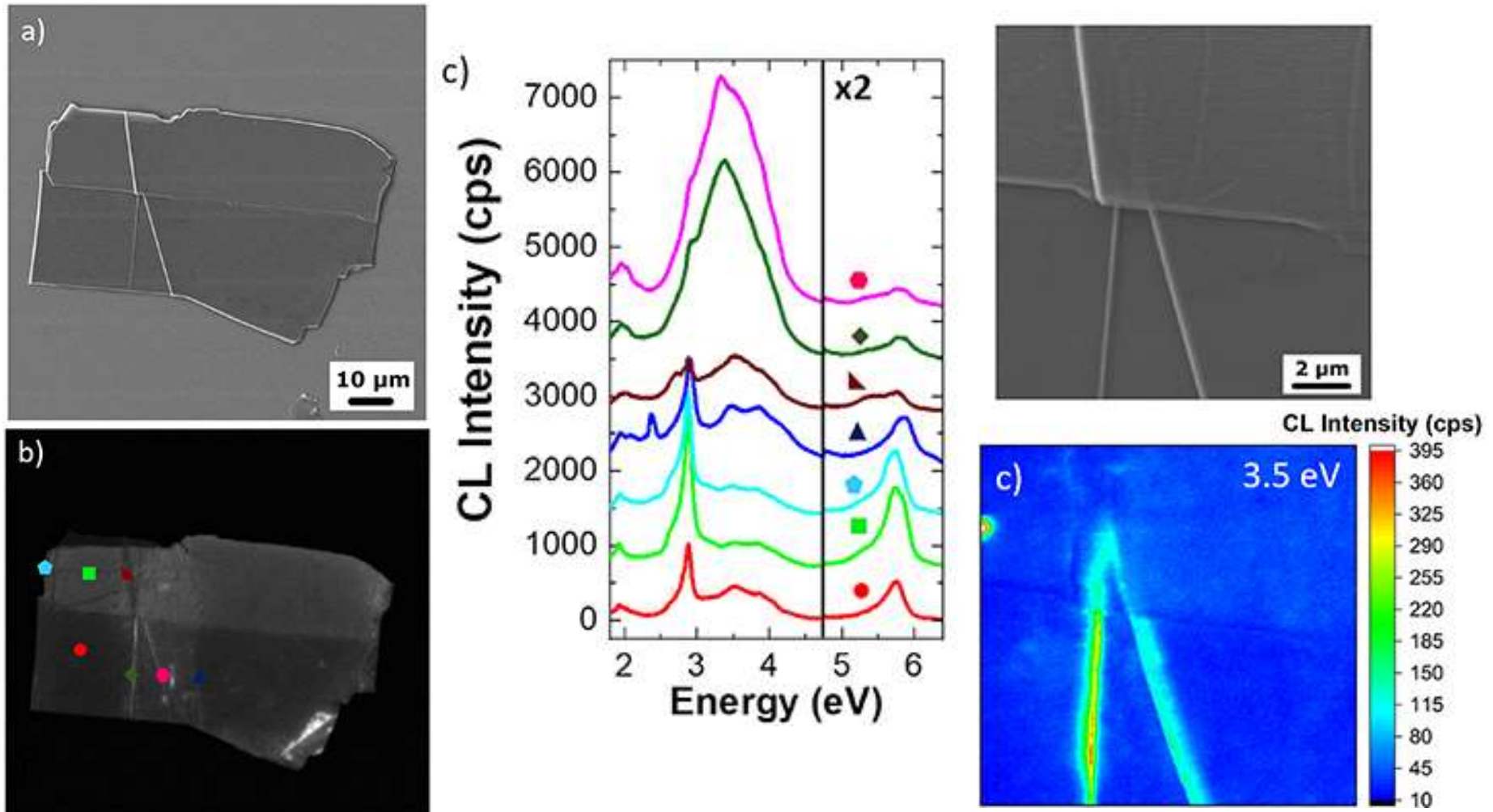
Multicolor Depth-Resolved Cathodoluminescence from Eu-Doped SiOC Thin Films



Optical Characterization of Implantation Defects

Electron penetration depth is variable: imaging buried structures

2D Materials 2022, **9**, 035018 **Light emission properties of mechanical exfoliation induced extended defects in hexagonal boron nitride flakes**



What are the ADVANTEGES of CL spectroscopy and imaging?

Detection of luminescence with different nature and their interaction

Correlative analysis with other electron excitation based techniques

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Nanoscale lateral resolution based on electron excitation

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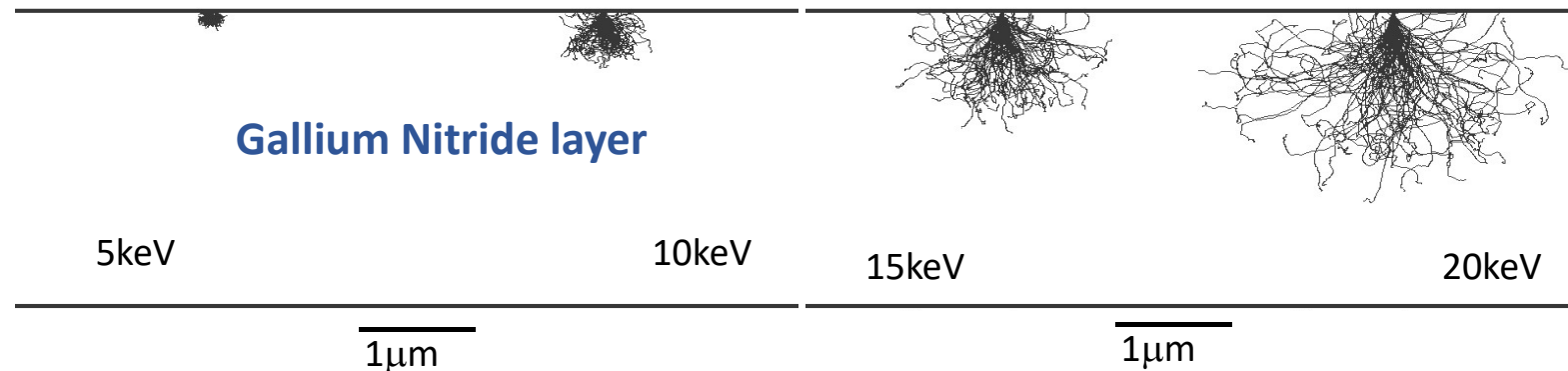
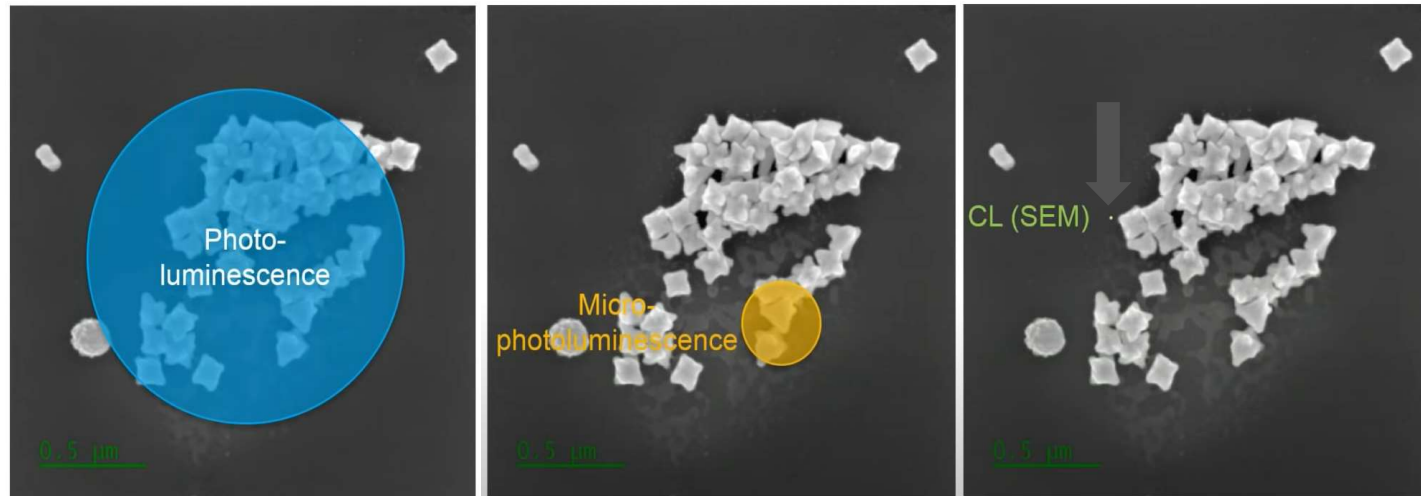
CL study of ion implanted materials

The case study: the luminescence of sulphur implanted silicon

Optical Characterization of Implantation Defects

Nanoscale lateral resolution based on electron excitation

The main feature, that allows the nanoscale lateral resolution of CL, is the size of the primary electron beam



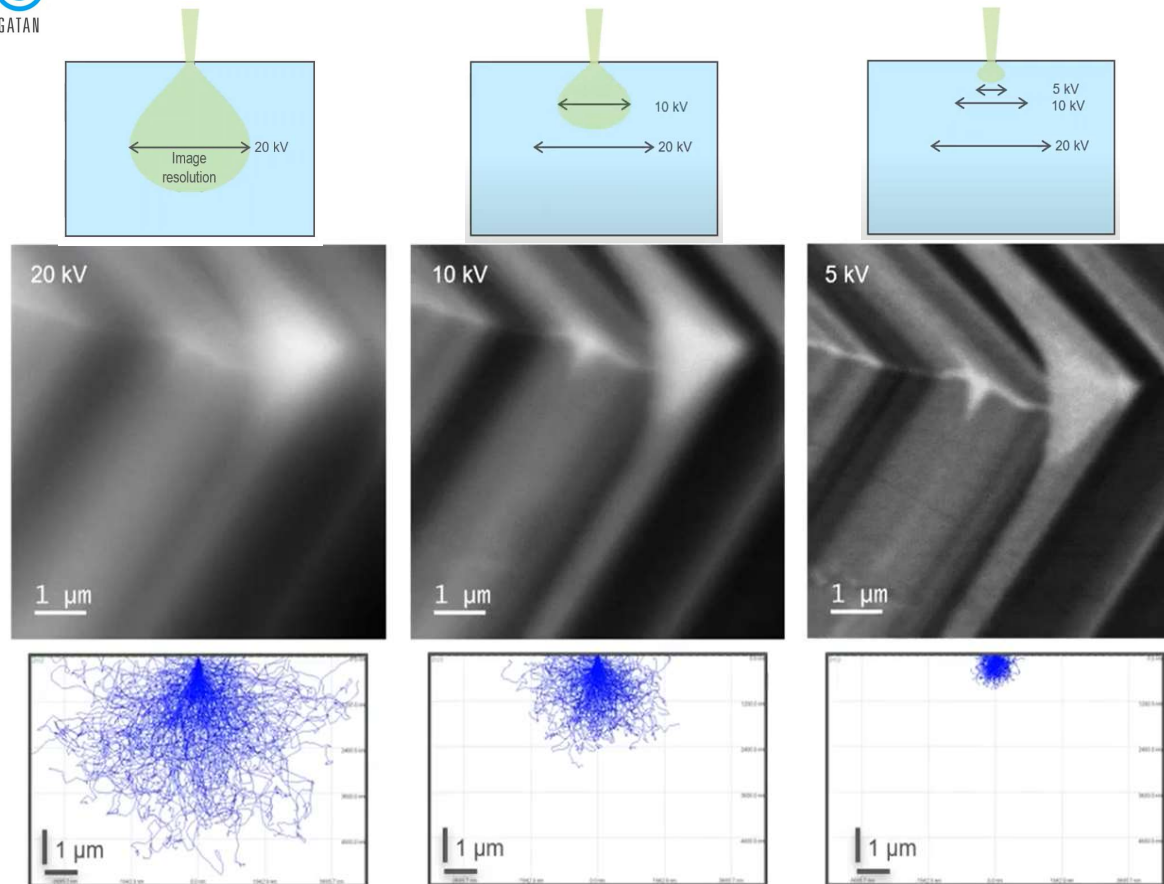
The main limiting factor is the interaction of the primary beam with the sample in analysis

Optical Characterization of Implantation Defects

Nanoscale lateral resolution based on electron excitation



CL Mapping of a Geological Sample



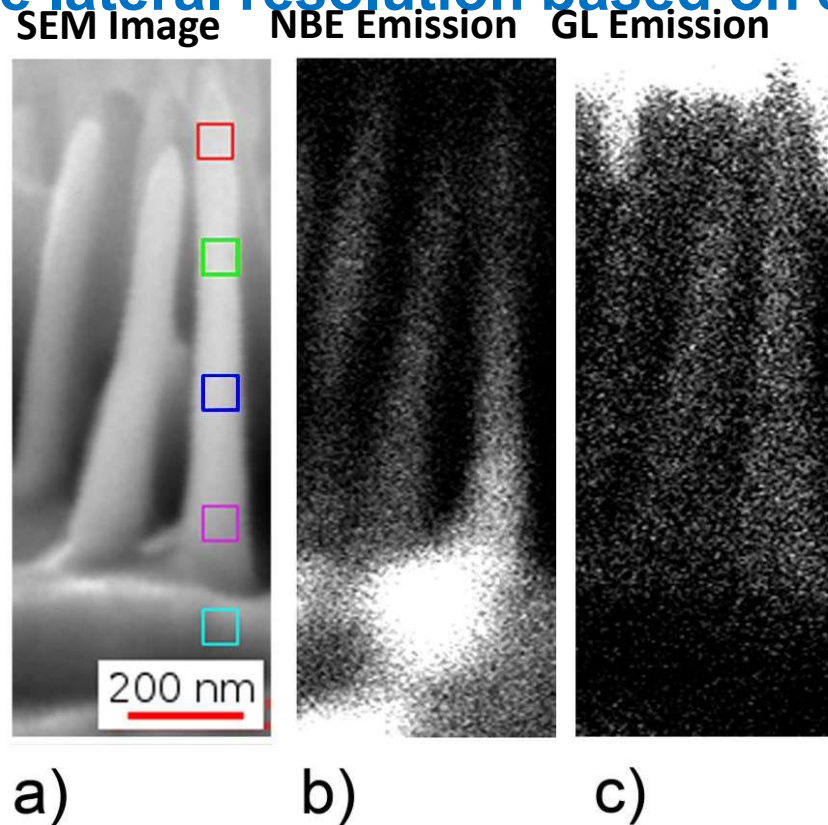
LATERAL RESOLUTION : the minimum detectable distance between two regions presenting different CL intensity.

It depends mainly on the size of the recombination volume (generation volume broadened for the diffusion length) of e-h pairs inside the material.

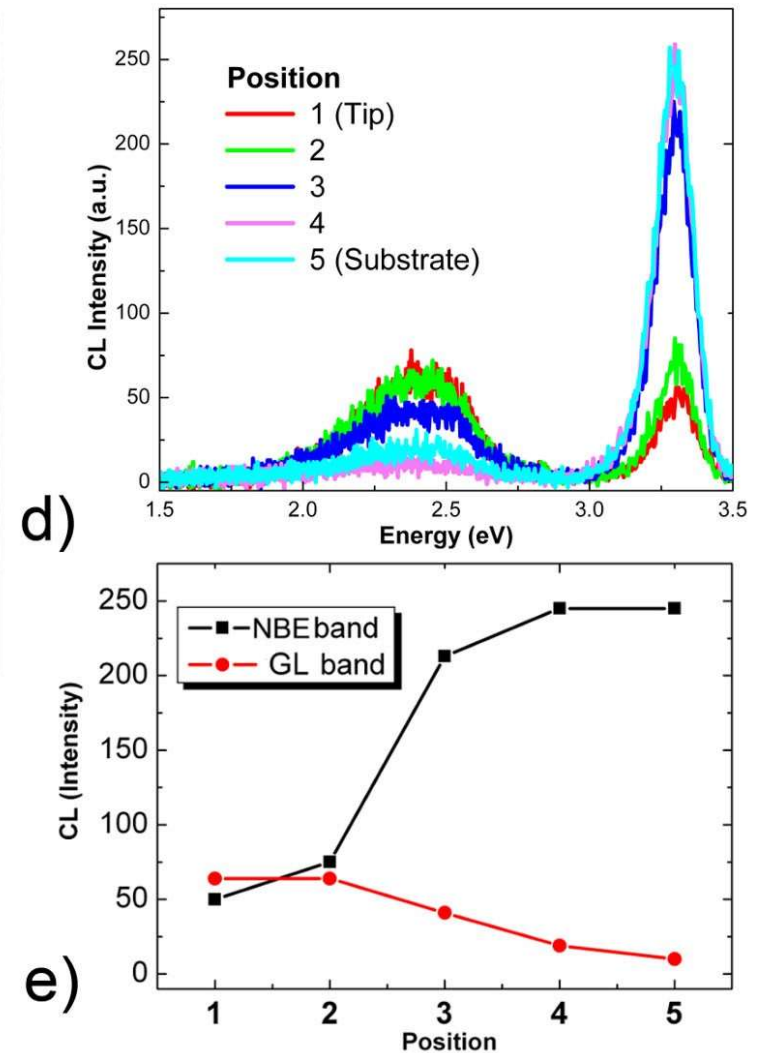
SPATIAL RESOLUTION IMPROVEMENT WITH LOWER ACCELERATING VOLTAGES

Optical Characterization of Implantation Defects

Nanoscale lateral resolution based on electron excitation



The nanoscale resolution of CL allows us to collect the CL spectra along a 100 nm ZnO NRs.

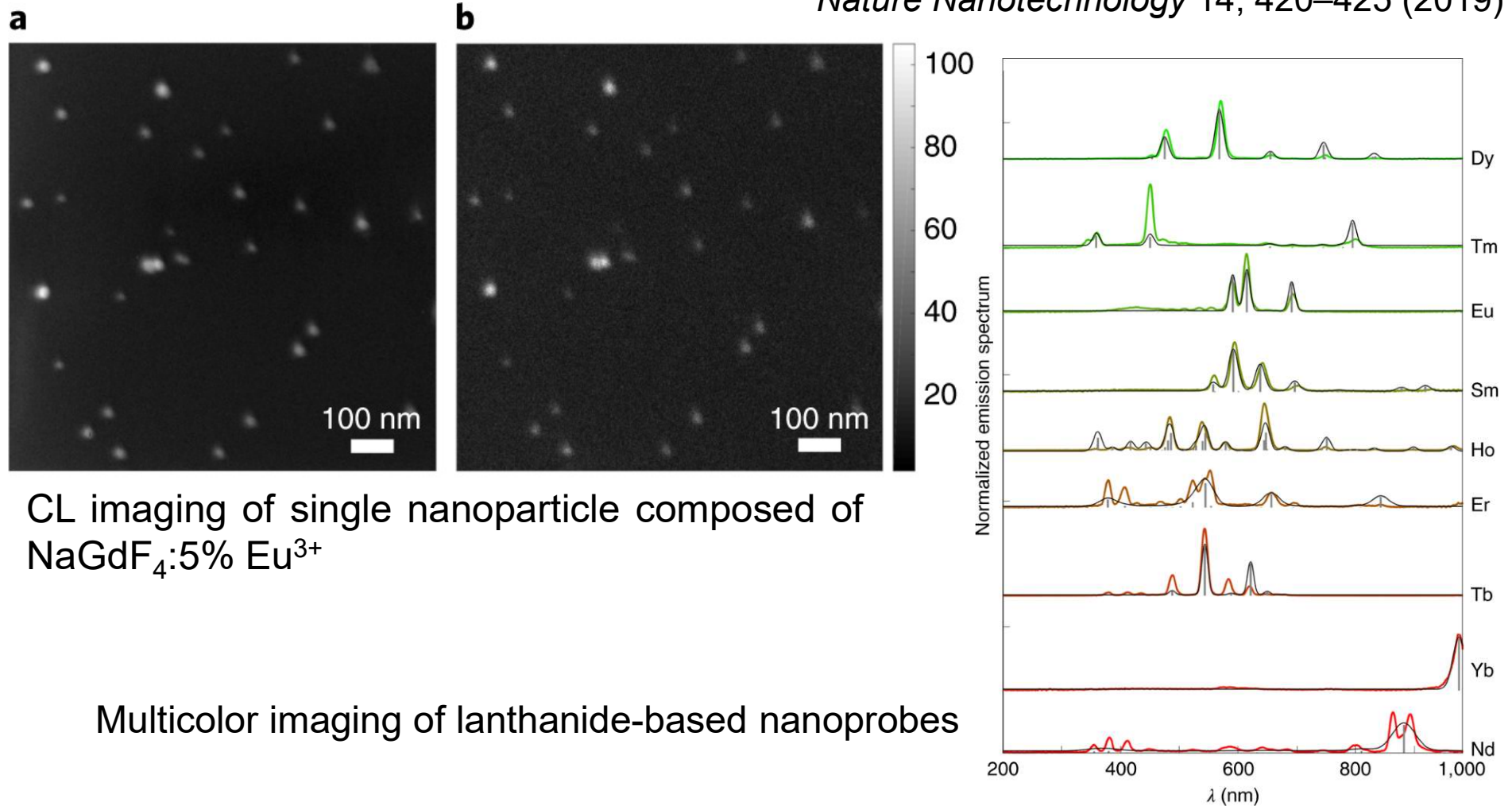


Optical Characterization of Implantation Defects

What is the limit of nanoscale detection resolution of SEM-CL?

Bright sub-20-nm cathodoluminescent nanoprobles for electron microscopy

Nature Nanotechnology 14, 420–425 (2019)



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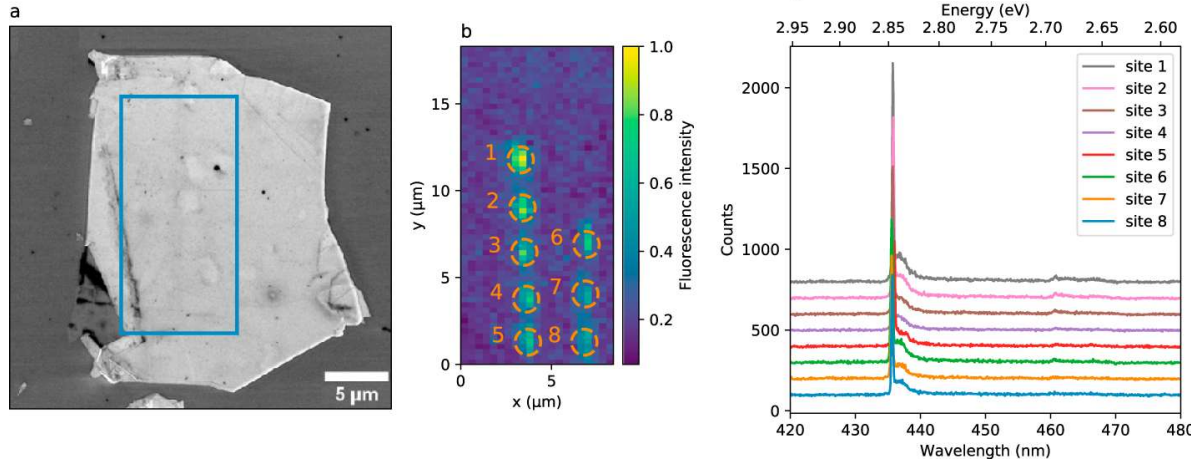
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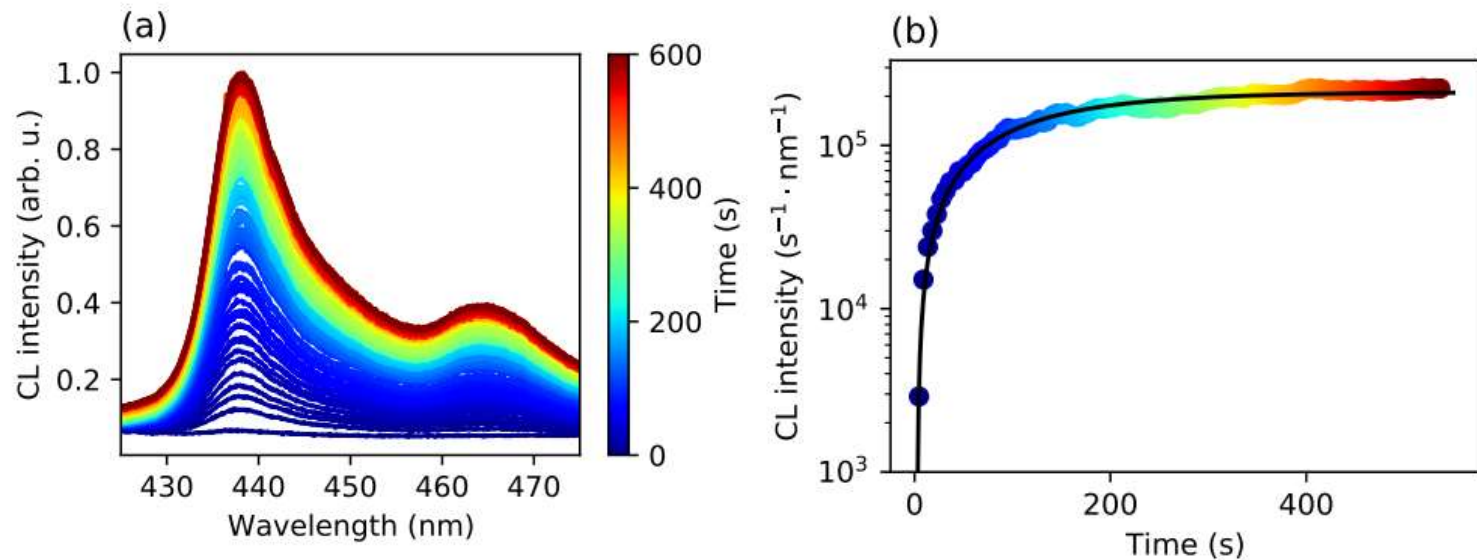
In-Situ CL analysis of electron irradiated materials



Single photon emitter (SPE), emitting in the blue, can be generated in hBN by electron beam irradiation.

Nature Communications
12, 3779 (2021)

In-Situ CL has been used to monitor the generation of the blue emitting center in electron irradiated hBN.



Appl. Phys. Lett. 121, 184002 (2022)

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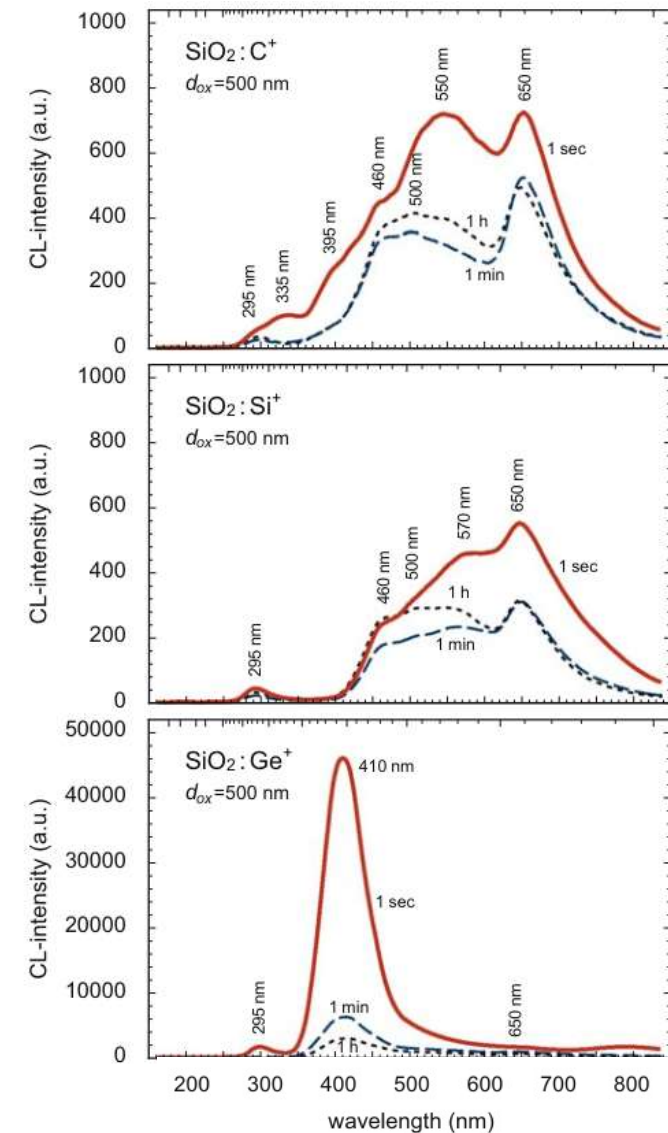
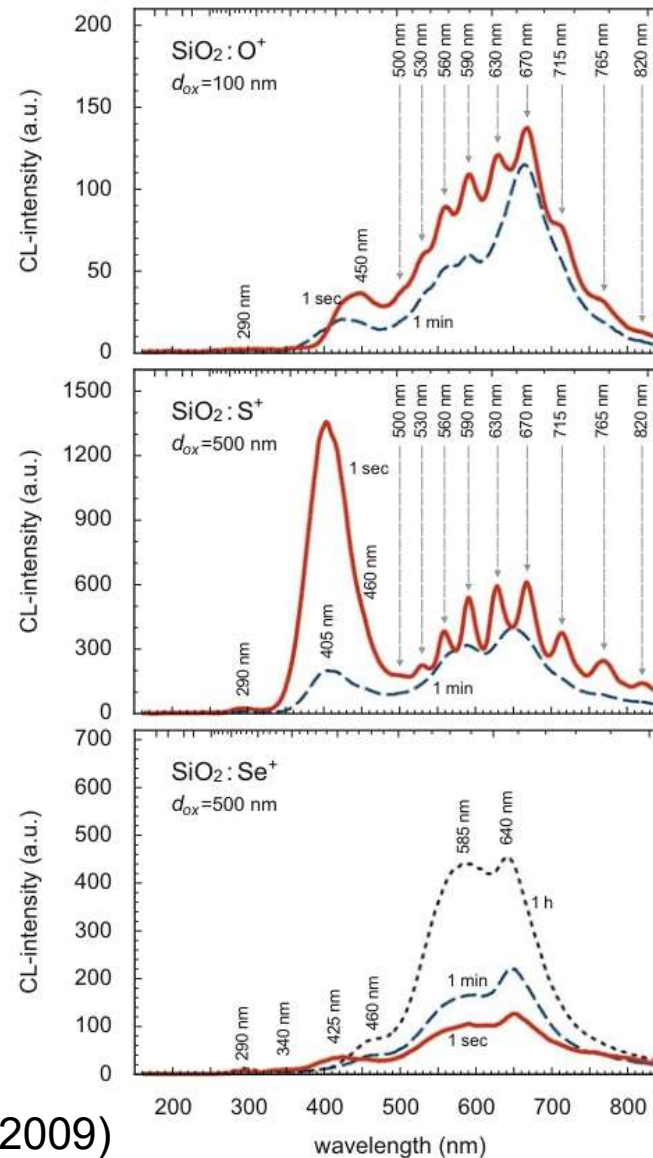
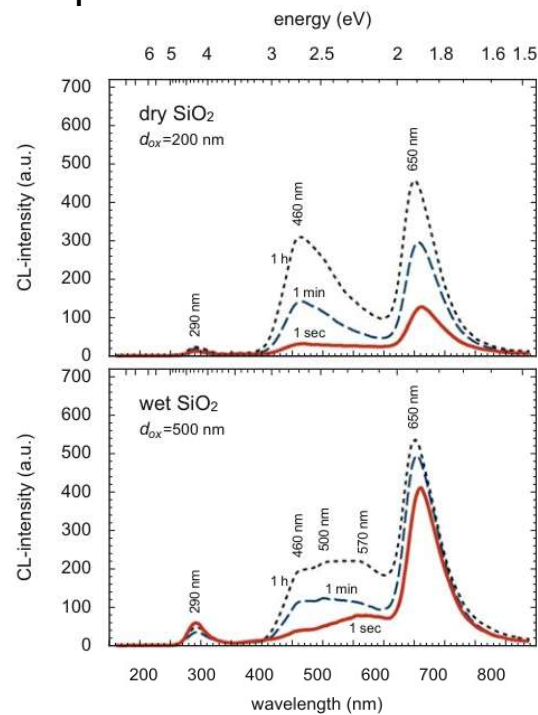
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Optical Characterization of Implantation Defects

CL study of ion implanted materials: Silicon Dioxide

SiO₂ is one of the most studied materials where the luminescence properties change drastically with ion implantation

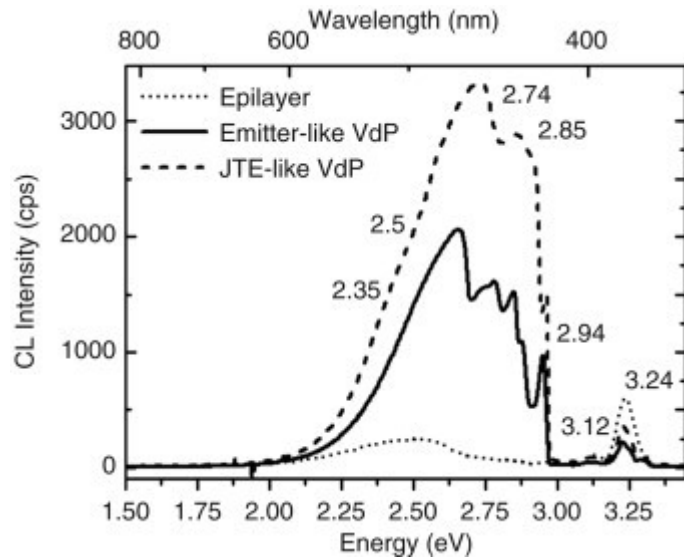


Jour. of Lum. **129**, 1488 (2009)

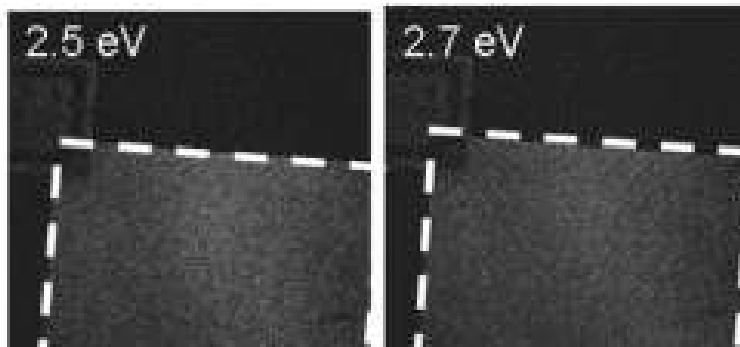
Optical Characterization of Implantation Defects

CL study of ion implanted materials: Silicon Carbide (4H-SiC)

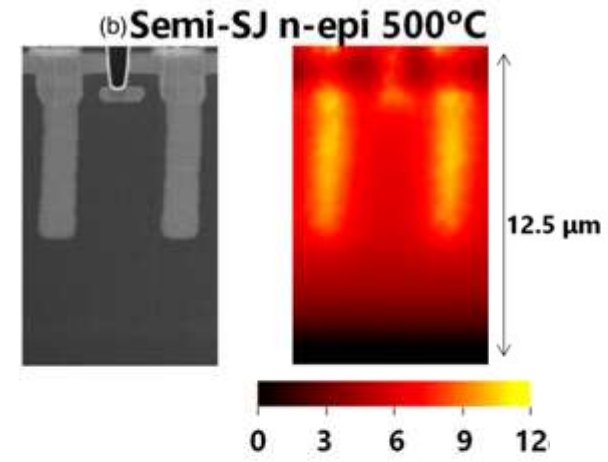
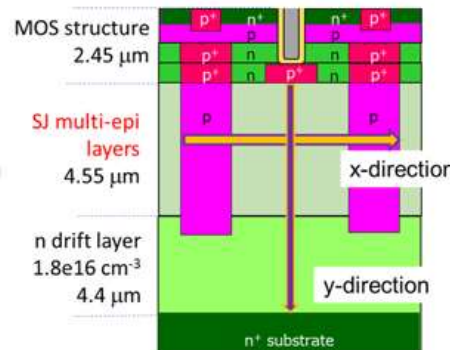
Superlat & Microstrut. **45**, 383 (2009)



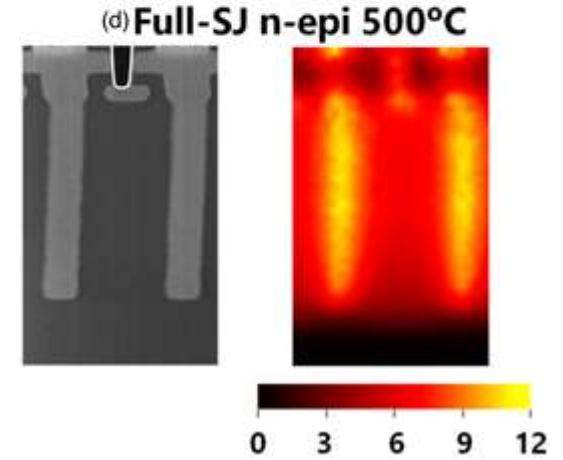
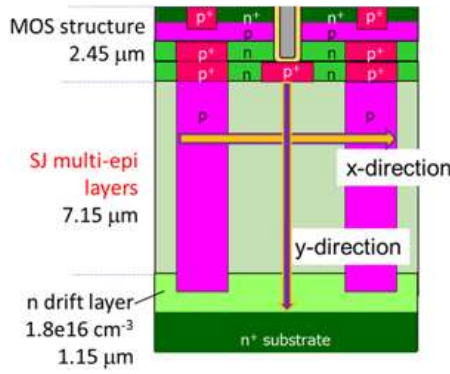
The Aluminum implantation in 4H-SiC, (employed for p doping) gives rise to a bright emission in the visible range, detectable in CL maps.



(b) Semi-SJ n-epi 500°C



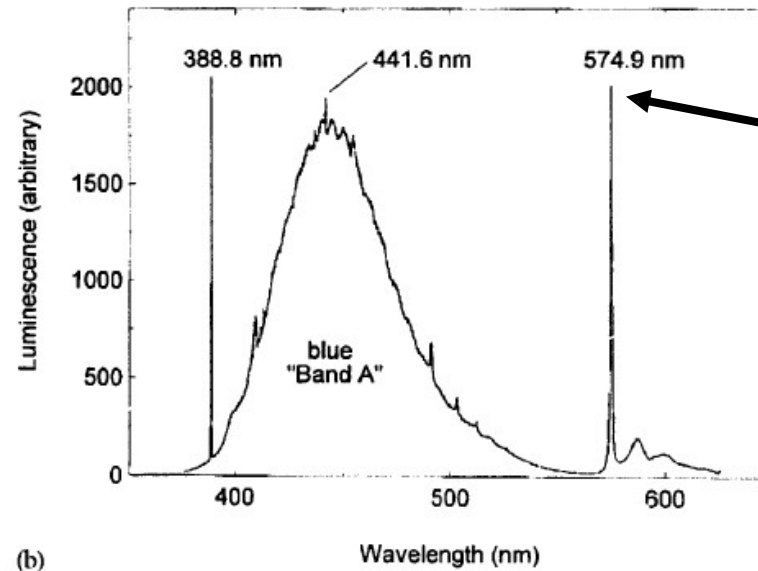
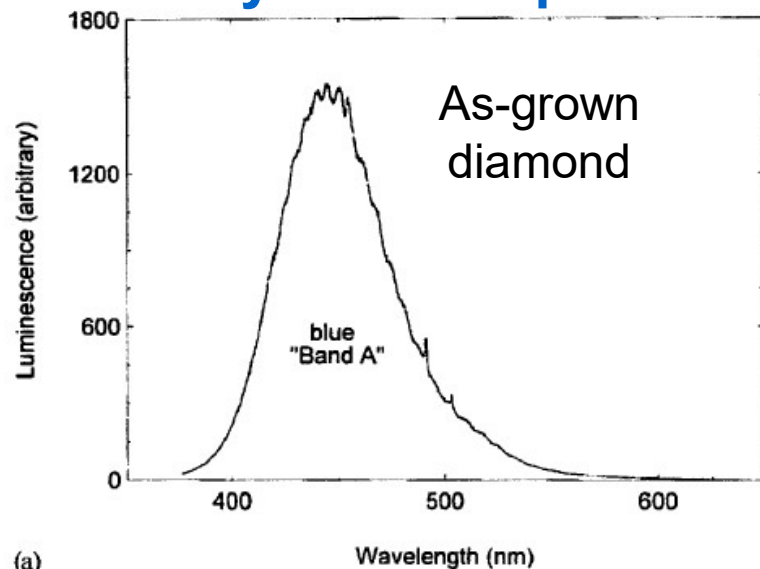
(d) Full-SJ n-epi 500°C



Cross-sectional CL maps are employed for quality benchmarking of complex 4H-SiC device fabrication
JJAP **62**, 016508 (2023)

Optical Characterization of Implantation Defects

CL study of ion implanted materials: Diamond

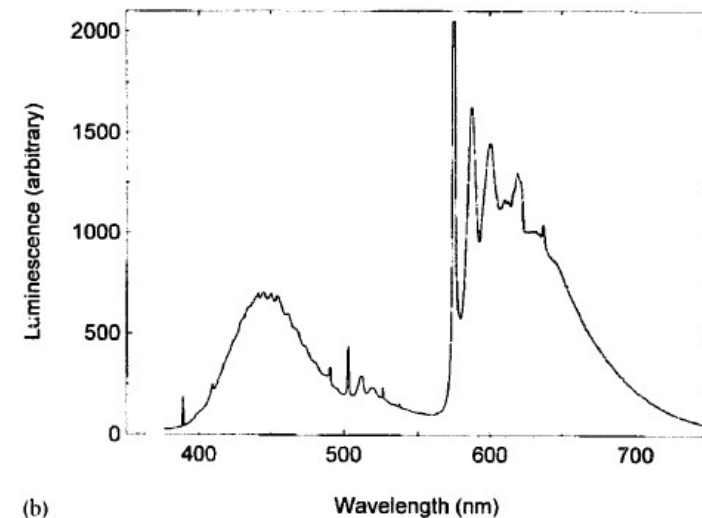


After first round of N implantation
(N-V)⁰

After second round of N implantation

Diamond (bandgap $E_g = 5.5$ eV) is a peculiar material, because the nitrogen ion implantation has a double purpose:

- First, the n type doping with high concentration
- Second the possible generation of sharp emission due to nitrogen related complex with single photon emission properties, employed in quantum cryptography



Diamond 6, 516-520 (1997)

What are the ADVANTEGES of CL spectroscopy and imaging?

Detection of luminescence with different nature and their interaction

Correlative analysis with other electron excitation based techniques

**Electron penetration depth is variable:
depth-resolved studies, imaging buried structures**

Nanoscale lateral resolution based on electron excitation

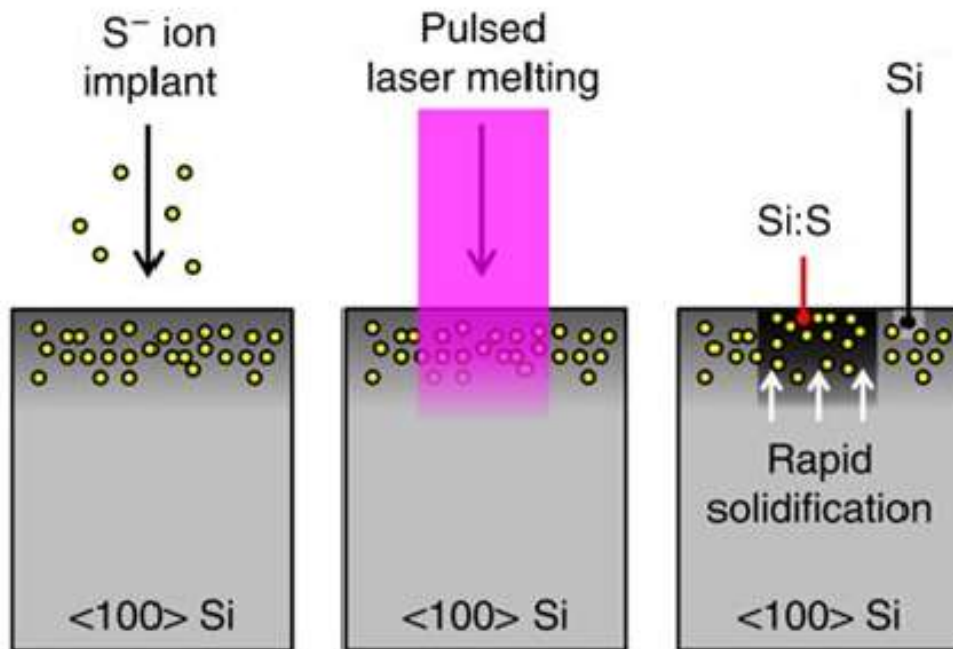
***In-Situ* CL analysis of electron irradiated materials**

Examples: CL study of ion implanted materials

The case study: the luminescence of sulphur implanted silicon

Optical Characterization of Implantation Defects

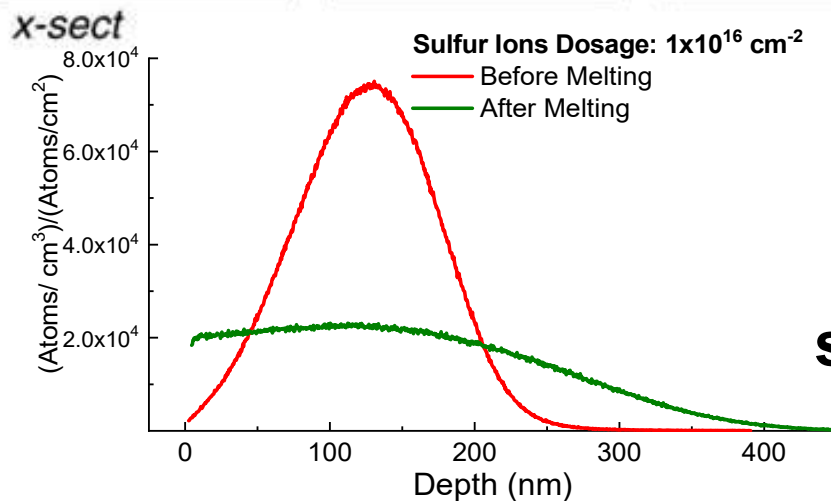
The case study: the luminescence of sulphur implanted silicon



Fabrication steps:

1- Ion implantation of sulphur ($^{32}\text{S}^+$) with a energy of 95 keV and 7° off-normal to prevent channeling.

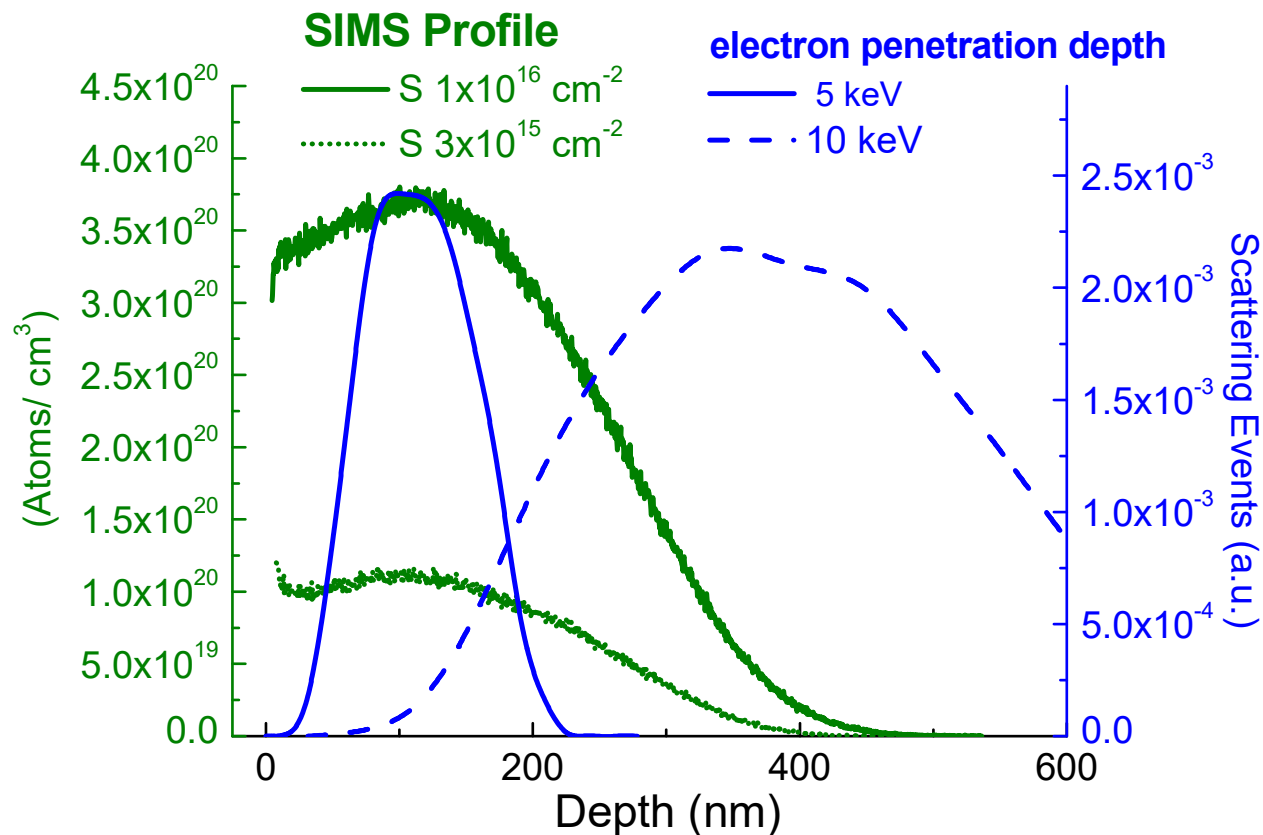
2- Pulsed laser melting (PLM) using a XeCl laser (308 nm, 4 50 ns long pulses with a power of 1.7 Jcm^{-2}).



This process results in a sulfur hyperdoping of silicon, with a doping concentration above the solubility limit of sulfur in silicon

Optical Characterization of Implantation Defects

The case study: the luminescence of sulphur implanted silicon

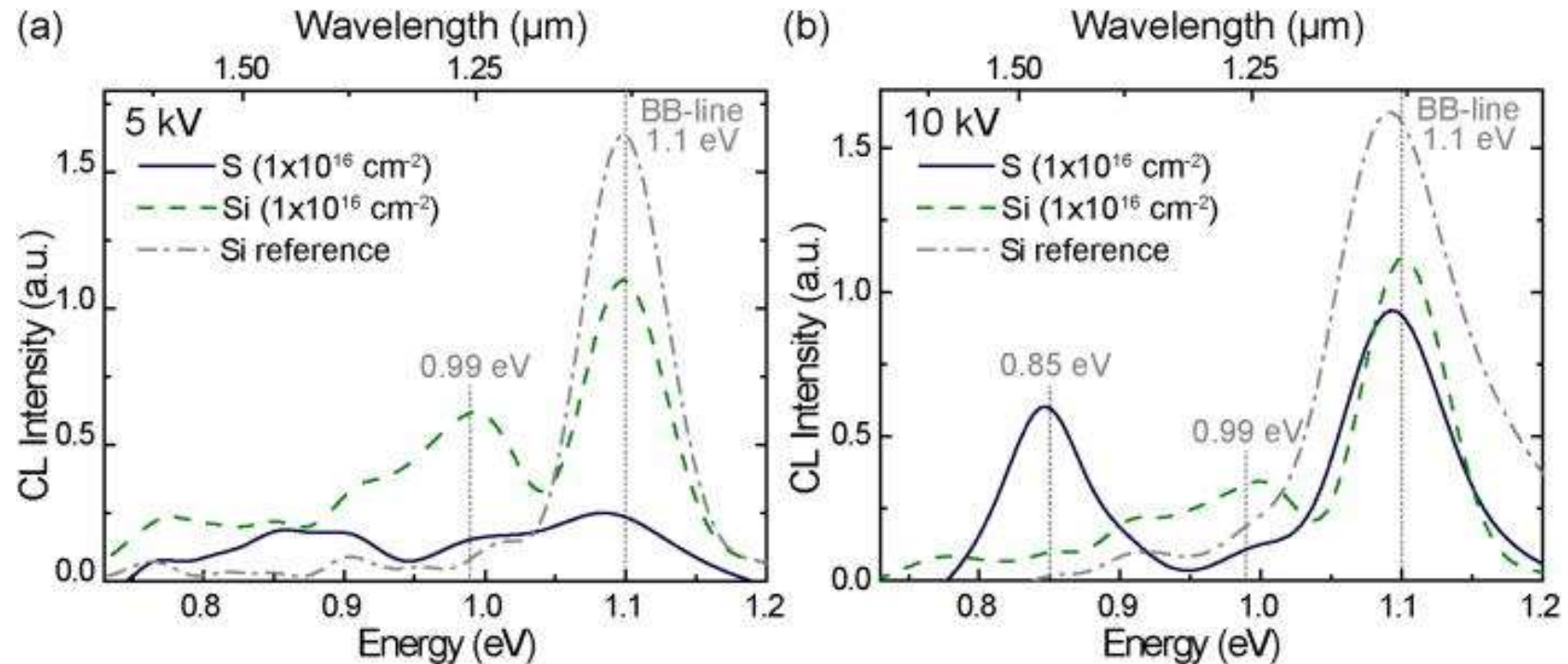


Montecarlo simulations are used to evaluate the electron penetration depth for choosing the accelerating voltage for cathodoluminescence analysis of the samples. We choose 5 keV and 10 keV CL analyses for probing the implantation plateau and implantation tail, respectively

Secondary ion mass spectroscopy (SIMS) is employed to determine the resulting sulfur concentration profiles for two different implantation doses. SIMS reveals a sulfur concentration above 10^{20} cm^{-3} with a hyperdoped layer thickness of 400 nm.

Optical Characterization of Implantation Defects

The case study: the luminescence of sulphur implanted silicon



In order to determine the intragap states caused by sulfur hyperdoping, we compare the CL spectra of the Si reference, Sulfur implanted Si and Silicon implanted Si to rule out the possible attribution to irradiation induced defects.

In particular:

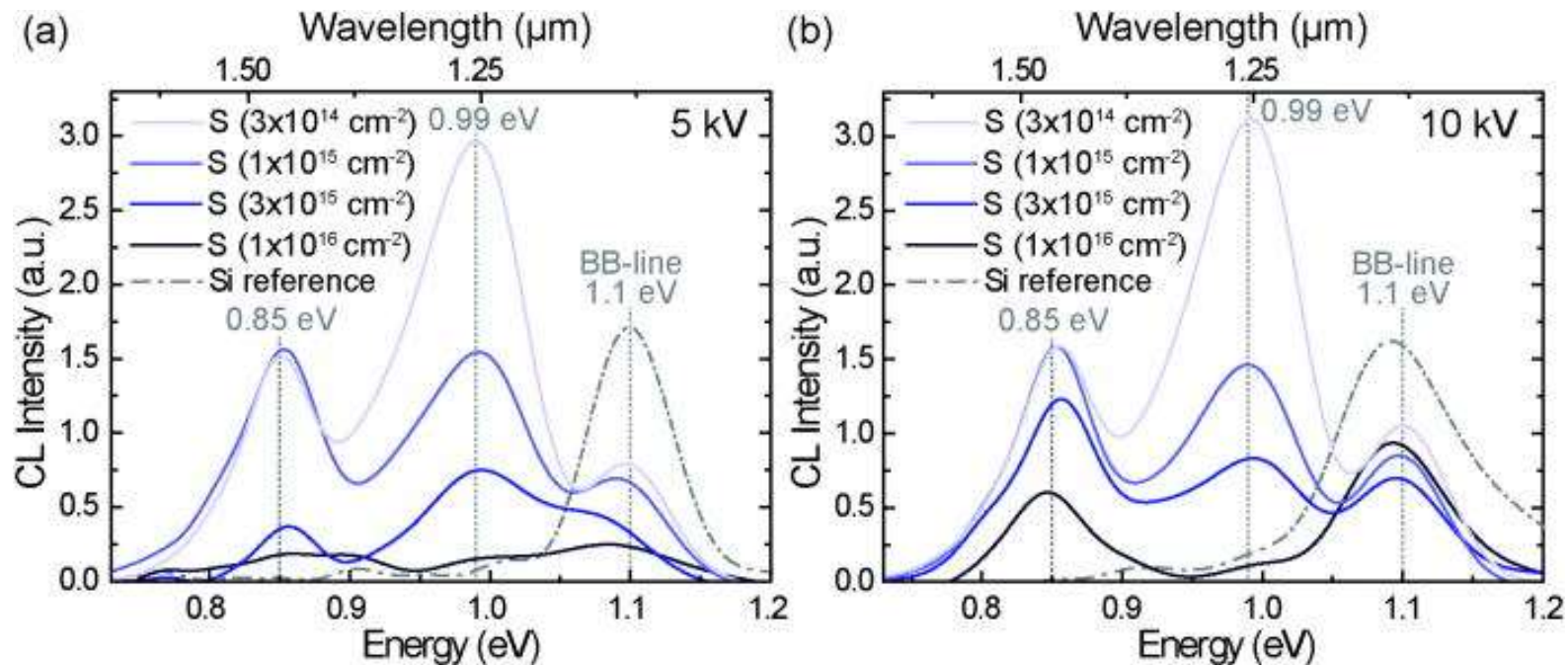
the 1.1 eV emission is the band-to-band recombination of silicon,

The 0.99 eV emission is assigned to silicon interstitial atoms,

The 0.85 eV emission is attributed the sulfur intragap state.

Optical Characterization of Implantation Defects

The case study: the luminescence of sulphur implanted silicon



Decreasing the sulfur concentration, we found the presence of irradiation induced deep levels, while the S related luminescence is maxed out in the implanted layer with the lowest S implantation dose.

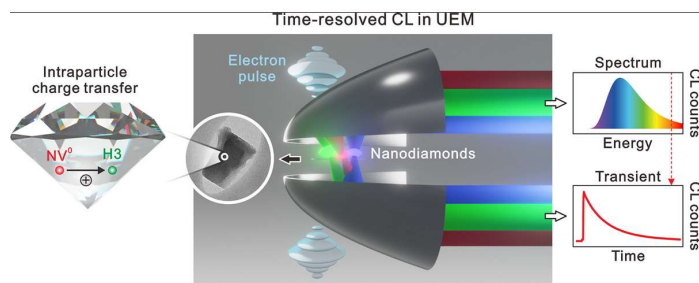
The decrease and broadening of the BB-line with the highest S dose in the implantation plateau is due to the presence of **strain** that cause the quenching of all the light emission. This effect does not occur in the implantation tail area due to the lower local concentration of S.

Optical Characterization of Implantation Defects

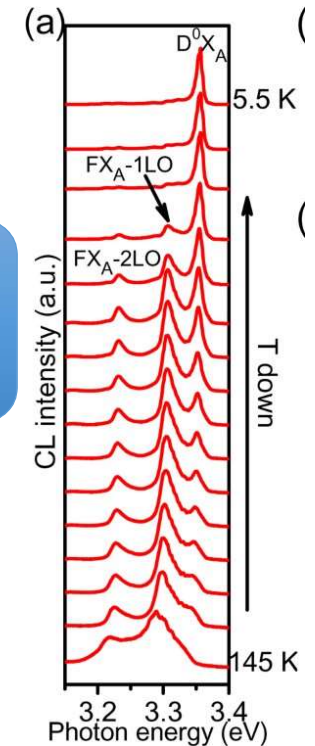
In this lesson, we only scratched the surface of the possible opportunities given by

cathodoluminescence spectroscopy and imaging

Time resolved
Cathodoluminescence

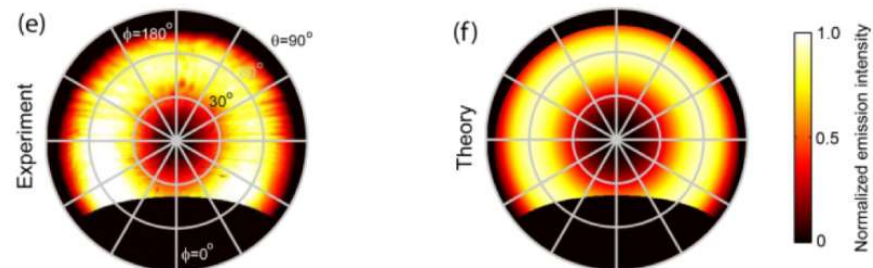


Temperature dependent
Cathodoluminescence

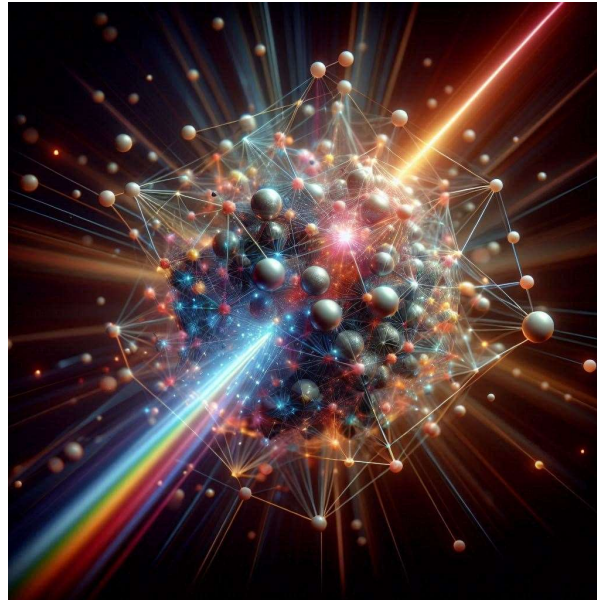


Angle resolved
Cathodoluminescence

Power dependent
Cathodoluminescence



Thank you for your attention



If you are interested in CL experiments, please contact me:

filippo.fabbri@nano.cnr.it

AS **Be** ST

A 7-Beryllium electron capture Study for nuclear and solid state physics